

# Experimental techniques in high-energy nuclear and particle physics

*“Dottorato di Ricerca in Ingegneria dell’Informazione”*

## **LECTURE 5.**

### **Tracking detectors**

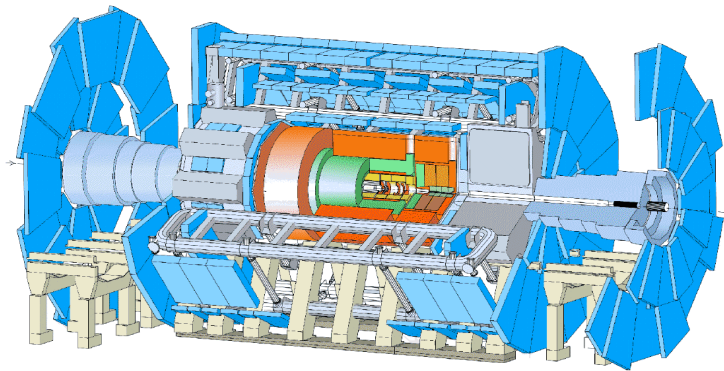
***Prof. Rino Castaldi***

**INFN-Pisa**

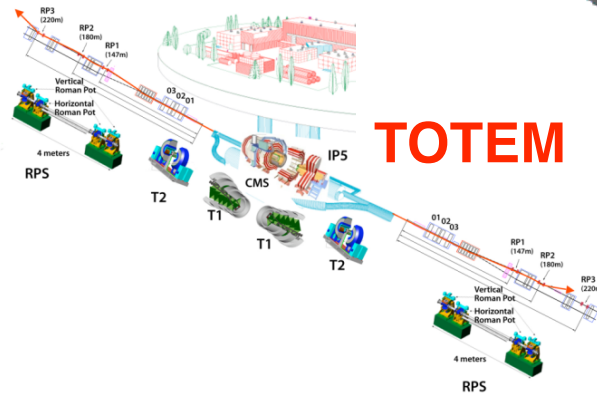
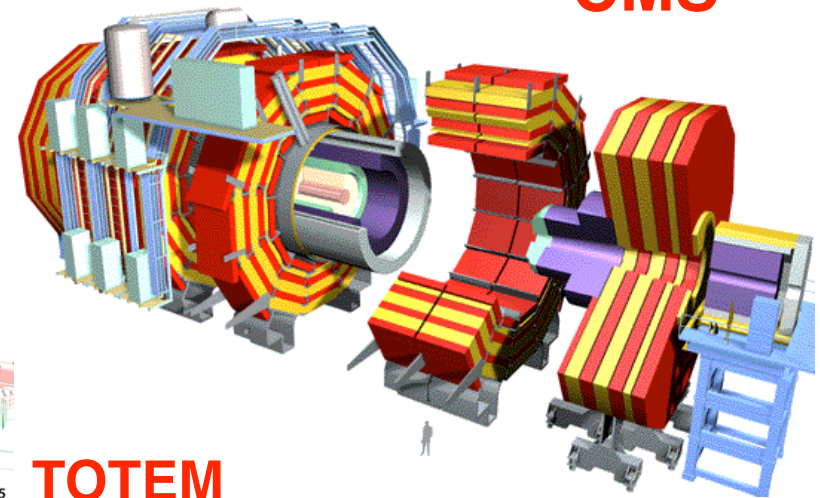
***[rino.castaldi@pi.infn.it](mailto:rino.castaldi@pi.infn.it)***

# The LHC Detectors

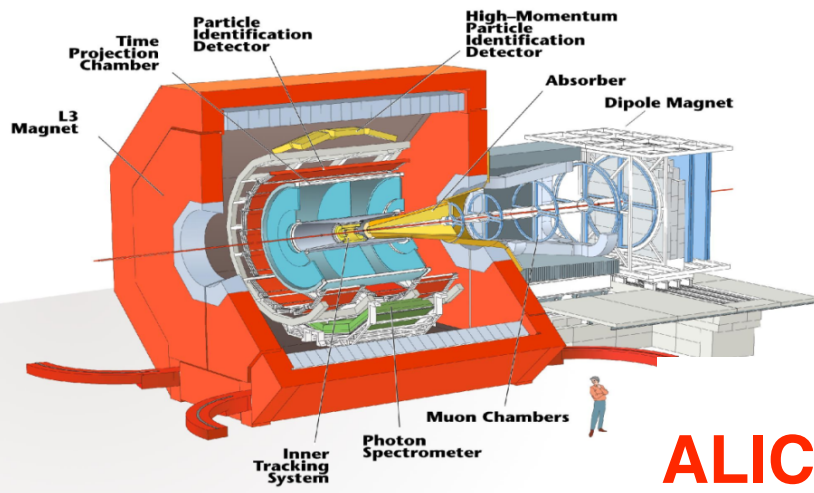
**ATLAS**



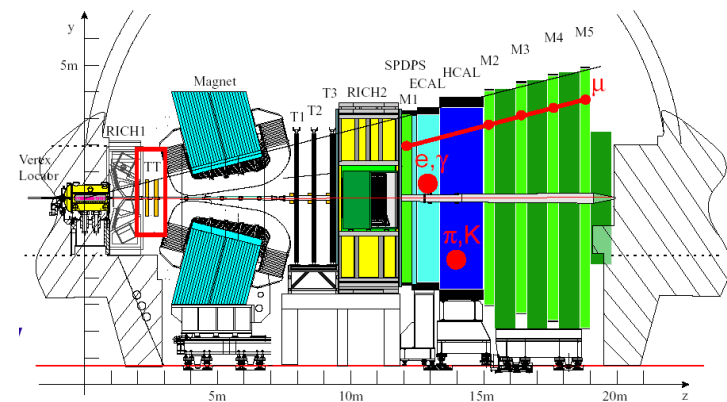
**CMS**



**TOTEM**



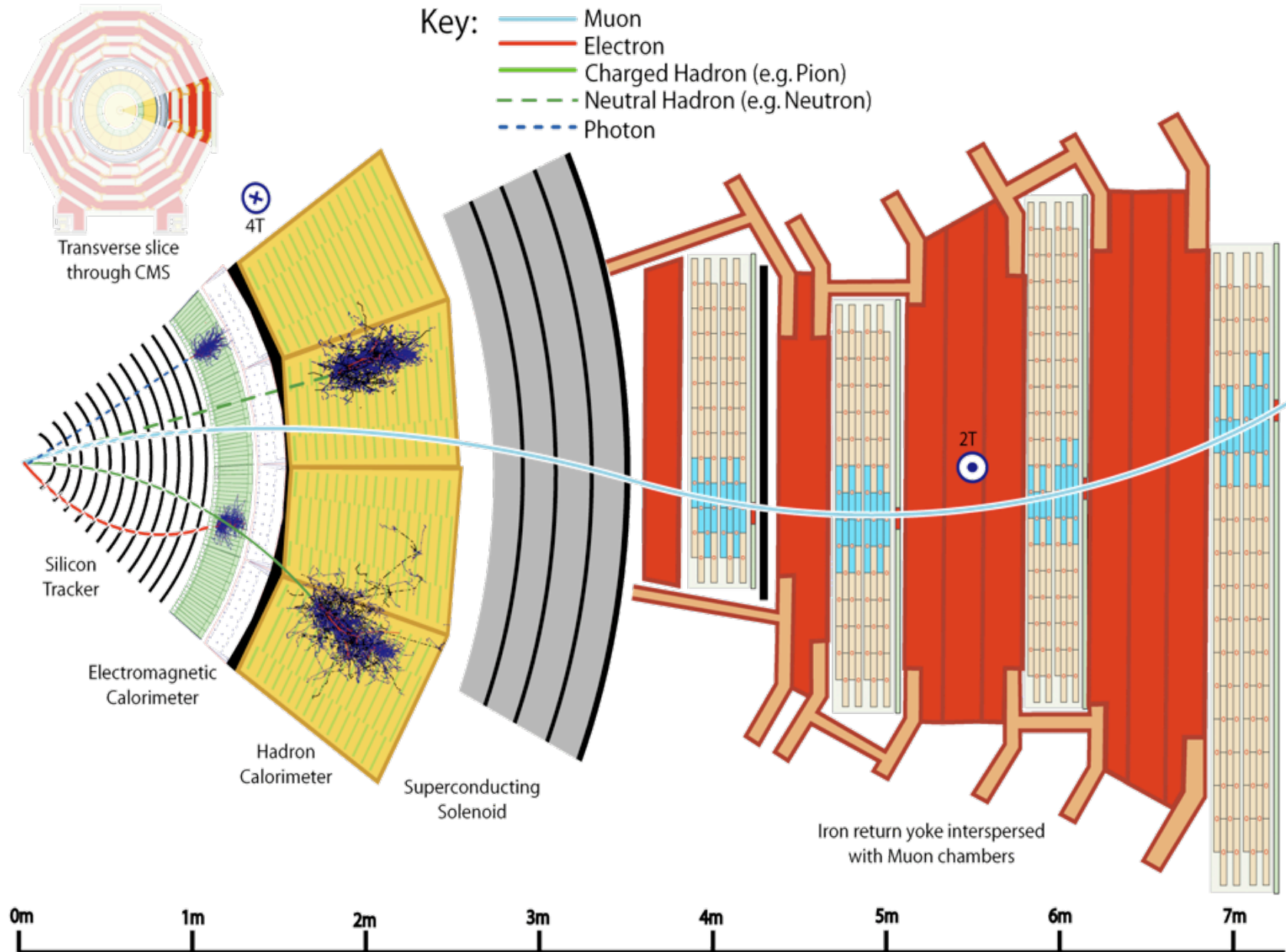
**ALICE**



**LHCb**



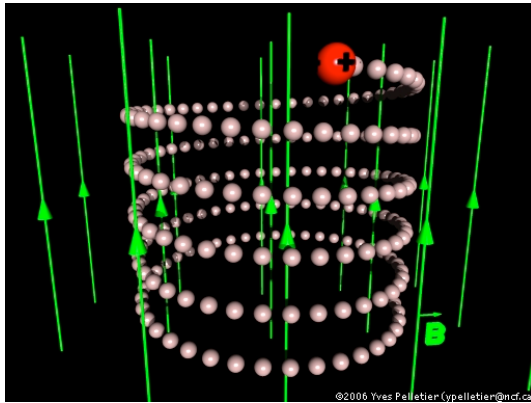
# Transverse slice of CMS



# Tracking: why

At hadron colliders the challenging aim is the full reconstruction of the events produced in the interaction under study. Therefore primary goals are:

- ✓ reconstruct the trajectories ("tracking") of charged particles and measure their momenta



Most common case: in a solenoidal uniform magnetic field the Lorentz force

$$\vec{F} = \frac{d\vec{p}}{dt} = q\vec{E} + q(\vec{v} \times \vec{B})$$

induce charged particles to follow a helicoidal path:

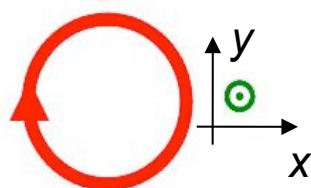
- describe circles in the transverse plane
- move uniformly along the magnetic field direction

$$p_T(\text{GeV}) = 0.3 B(\text{T}) R(\text{m})$$

- ✓ identify the sign of the charge

**Positives**

+

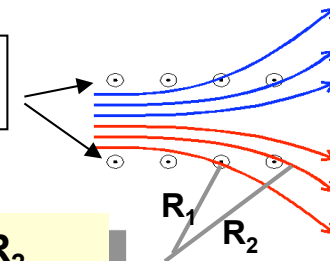


**Negatives**

-



Magnetic field, pointing out of the plane



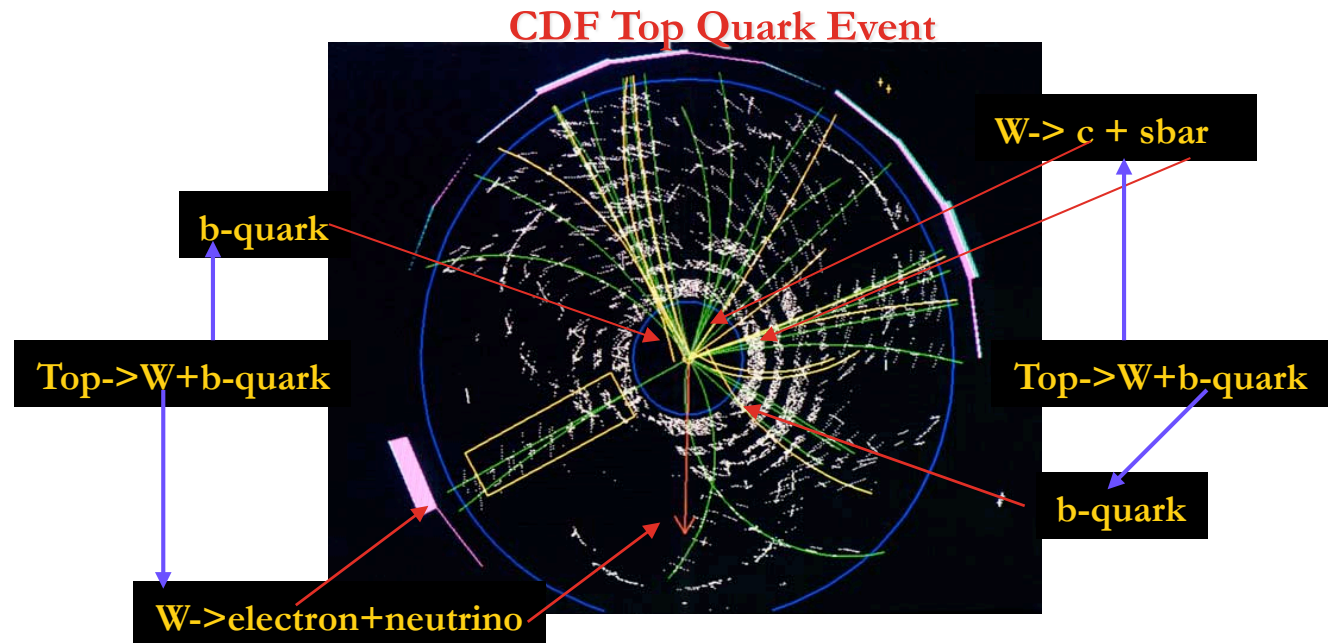
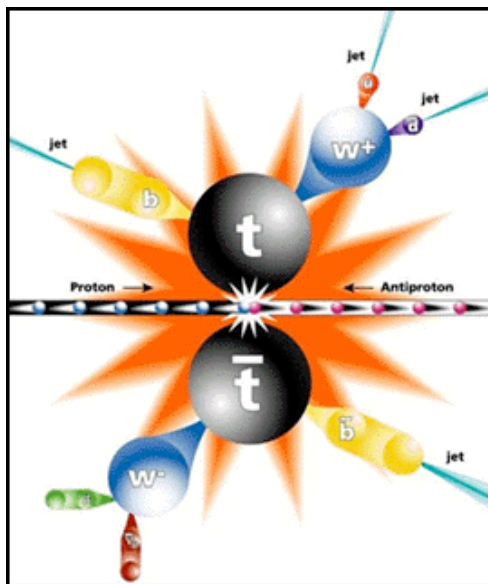
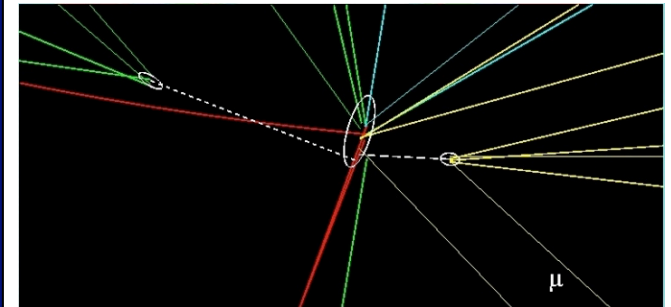
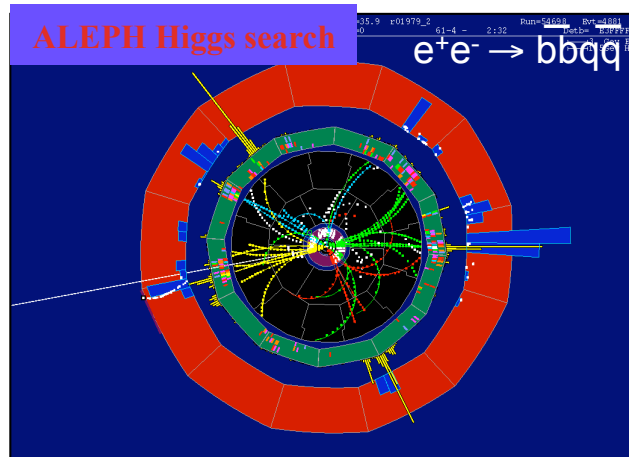
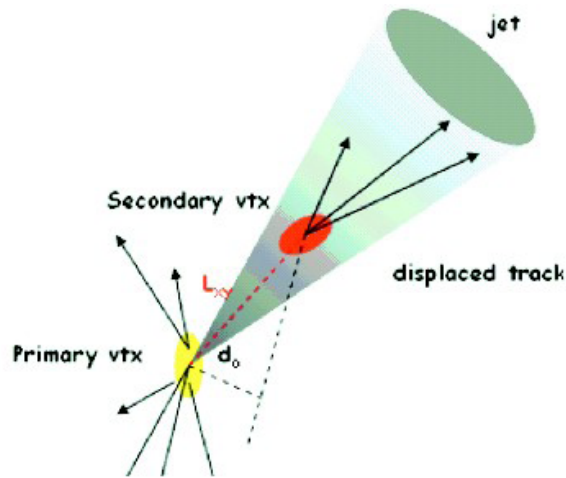
negative charge

positive charge

$$p_1 < p_2 \Leftrightarrow R_1 < R_2$$

# Tracking: why

✓ reconstruct the primary and secondary vertices of the interaction  
(at LHC with large pile-up of events in the same bunch crossing !)



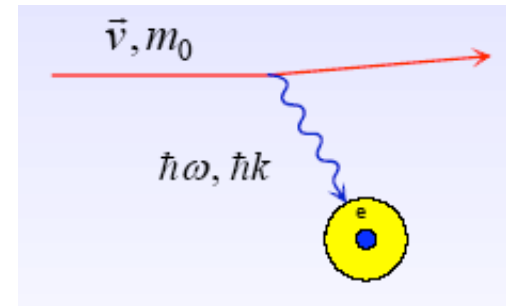
# Tracking: a real challenge at LHC

- Tracking at LHC is a very complex procedure due to the high track density. It needs specific implementation adapted to the detector type and geometry
- Precise and efficient detector modules are required to measure where the particle crossed the module
- Fast and radiation hard detectors and electronics are needed
- Track reconstruction requires specific software implementation:
  - track finding (pattern recognition)
  - estimation of track parameters (fitting)
- Precise alignment of detector modules is a prerequisite for efficient tracking

# Tracking: how

measurable signals occur via the interaction of charged particles with the detector material.

Dominant interaction is due to the coulomb interactions with the atomic electrons of the detector.

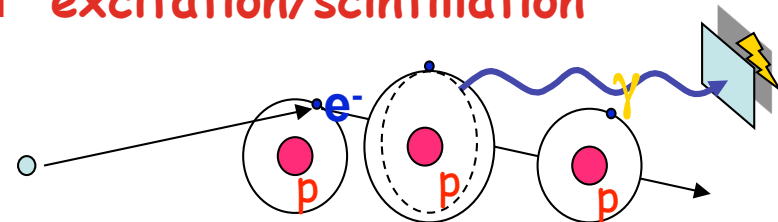
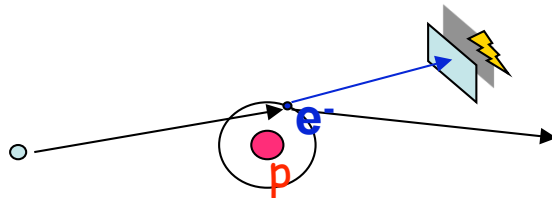


Depending on the  $\hbar\omega$  value we may have:

□ ionization

or

□ excitation/scintillation



Ionization and excitation of atomic electrons in matter are the most common processes and allow to build precise tracking detectors .

# Ionization: the Bethe-Bloch formula

$$\left\langle \frac{dE}{dx} \right\rangle = -4\pi N_A r_e^2 m_e c^2 z^2 \frac{Z}{A} \frac{1}{\beta^2} \left[ \frac{1}{2} \ln \frac{2m_e c^2 \gamma^2 \beta^2}{I^2} T^{\max} - \beta^2 - \frac{\delta}{2} \right]$$

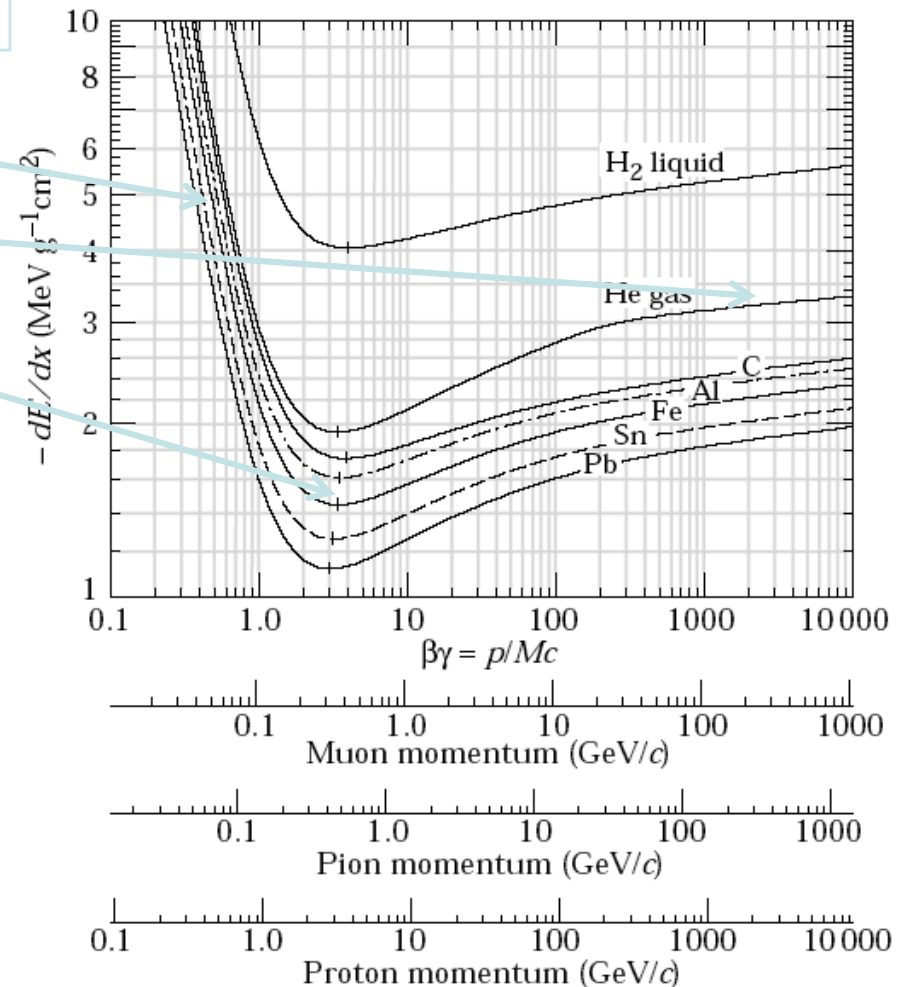
$$T_{\max} \approx 2m_e c^2 \beta^2 \gamma^2 \quad \left[ -\frac{dE}{dx} \approx K q^2 \frac{Z}{A \beta^2} \left[ \ln \frac{2m_e c^2 \beta^2 \gamma^2}{I^2} - \beta^2 \right] \right]$$

Characterized by:

- a fall off at low energy  $\sim 1/\beta^2$
- a relativistic rise  $\sim \ln \beta\gamma$
- a minimum at  $\beta\gamma \approx 3$
- depends only on  $\beta\gamma$  not on  $m$

High energy charged particles lose energy **slowly** in material due to ionization leaving tracks as they pass ( For  $Z \approx 0.5A$  at  $\beta\gamma \approx 3$   $1/\rho \, dE/dx \approx 1.4 \text{ MeV cm}^2/\text{g}$  )

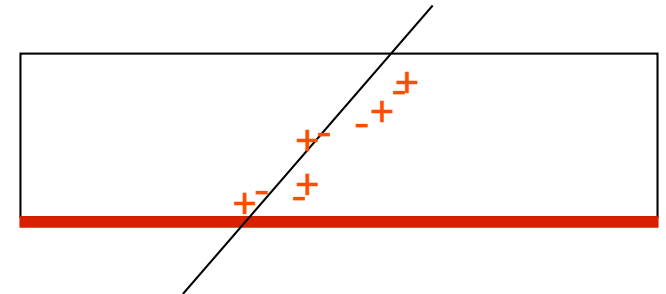
→ many kinds of tracking detectors can be done !



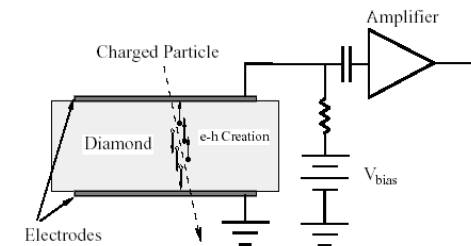


# Tracking Detectors

Charged particles crossing a material lose energy by ionizing (and exciting) atoms and thus leaving along their path a trace of electron-ion pairs in gases and liquids and electron-hole pairs in solids.



Measurable electronics signals can be induced by the charges produced in this way and can be read by dedicated electronics



□ In solid state detectors the charges produced by the ionization due to the incoming particle are sufficient to provide a measurable signal.

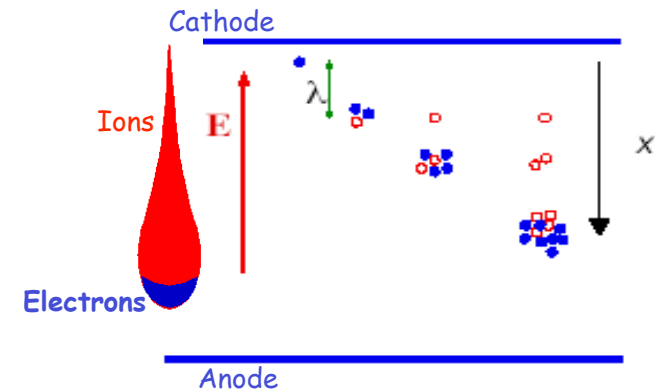
□ In gas detectors the charges produced by the primary ionization due to the incoming particle need amplification in order to provide a measurable signal.

- Mean (most probable) energy loss: 116 (78) keV for 300 $\mu$ m Si thickness
- 3.6 eV to create an e-h pair  
 $\Rightarrow$  72 e-h/ $\mu$ m (mean)  
 $\Rightarrow$  108 e-h/ $\mu$ m (most probable)
- Mean charge (300 $\mu$ m Si)  
 $\approx$  22000 e  $\approx$  3.6 fC

GAS )	Helium	Argon	Xenon	CH <sub>4</sub>	DME
dE/ dx (keV/ cm)	0.32	2.4	6.7	1.5	3.9
<n>(ion-pair/ cm)	5.9	29	44	16	55

# Gas Detectors: the avalanche multiplication

As the electric field increases to sufficient high value ( $\sim 100\text{kV/cm}$ ) more and more electrons gain kinetic energy in excess of the ionization energy so that they can ionize in turn other atoms (secondary ionization) and so on.



The mean free path  $\lambda$  is defined as the average distance that an electron must walk before another ionizing collision may occurs. On average every  $\lambda$  the number of ion pairs is doubled.  $\alpha=1/\lambda$  is called Townsend coefficient:

$$dN = N \alpha dx$$

$$N(x) = N_0 \exp(\alpha x) \quad N/N_0 = A = \text{Amplification or Gas Gain}$$

The problem with an avalanche multiplication with an homogeneous electric field is that very high field on are needed and may easily cause breakdown

The solution is to obtain the avalanche multiplication in an inhomogeneous field:

$$\alpha(E) \rightarrow N(x)/N_0 = A = \exp\left[\int \alpha(E(x')) dx'\right]$$

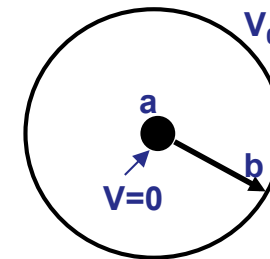
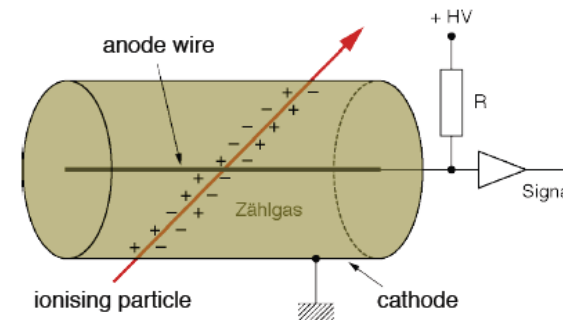
# Wire Chamber: Electron Avalanche

- Basic design: ionization chamber with HV sense wire

Typically a gas detector will have ~20 primary ions per cm created by a track: amplification needed in order to provide a measurable signal.

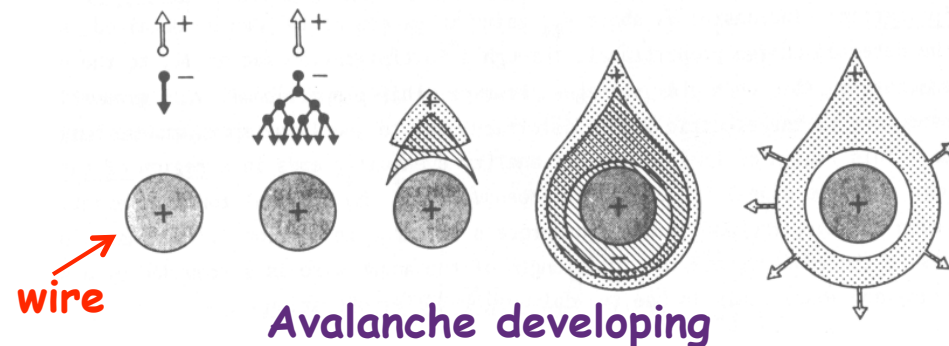
Consider a thin wire with radius  $a$  ( $10\text{-}25\mu\text{m}$ ) at voltage  $V=0$  in a tube of outer radius  $b$  ( $1\text{-}3\text{cm}$ ) voltage  $V_0$ . The electric field inside the tube is given by:

$$E = 2\lambda/r, \quad V_0 = 2\lambda \ln(b/a), \quad V(r) = V_0 \frac{\ln(r/a)}{\ln(b/a)}, \quad E(r) = \frac{V_0}{r \ln(b/a)}$$

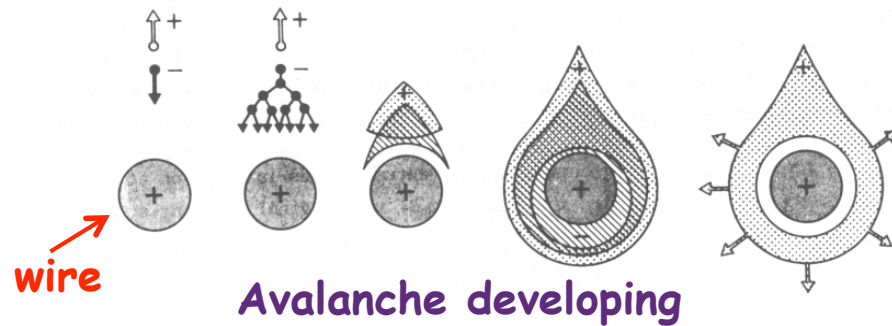


Example:  $V_0=1000\text{V}$ ,  $a=10\mu\text{m}$ ,  $b=10\text{mm}$ ,  
 $E(a)=150\text{kV/cm}$

Electric field is sufficient to accelerate electrons to energies which are sufficient to produce secondary ionization  $\rightarrow$  electron avalanche  $\rightarrow$  signal.  
 (typical amplification:  $10^3\text{-}10^5$ )



# Wire Chamber: Signals from Electron Avalanches



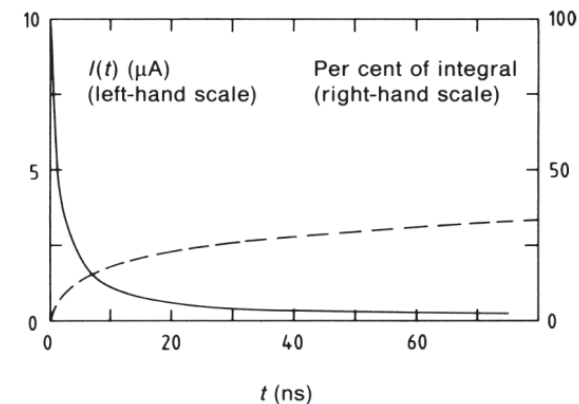
The electron avalanche happens very close to the wire. First multiplication only around  $R = 2 \times$  wire radius. Electrons are moving to the wire surface very quickly ( $\ll 1\text{ns}$ ). Ions are drifting slowly towards the tube wall (typically several  $100\mu\text{s}$ ).

The signal is characterized by a very fast 'spike' from the electrons and a long ion tail.

The total charge induced by the electrons amounts to 1-2% of the total induced charge.

Signal due to ions dominates, as they travel all the way to the cathode.

The signal is characterized by a very fast peak from the electrons and a long ion tail.



# Amplification vs applied voltage

- ❖ Average energy lost in creating ion pair  $\sim 10\text{-}20$  eV.
- ❖ Primary ionization: number of ionizing collisions per unit length for the incident particle. (Poisson distribution)
- ❖ Secondary ionization: the electric field is sufficient to accelerate electrons to energies which are sufficient to produce secondary ionization

For intermediate value of the electric field the number of electrons produced in the avalanche is proportional to the primary ionization ( amplification  $A \approx 10^3\text{-}10^4$  ; Landau distribution)

Increasing the electric field the amplification increases but the detector is not working anymore in a proportional regime:

$A \approx 10^4\text{-}10^5$  Semi proportional region due to space charge screening around the anode

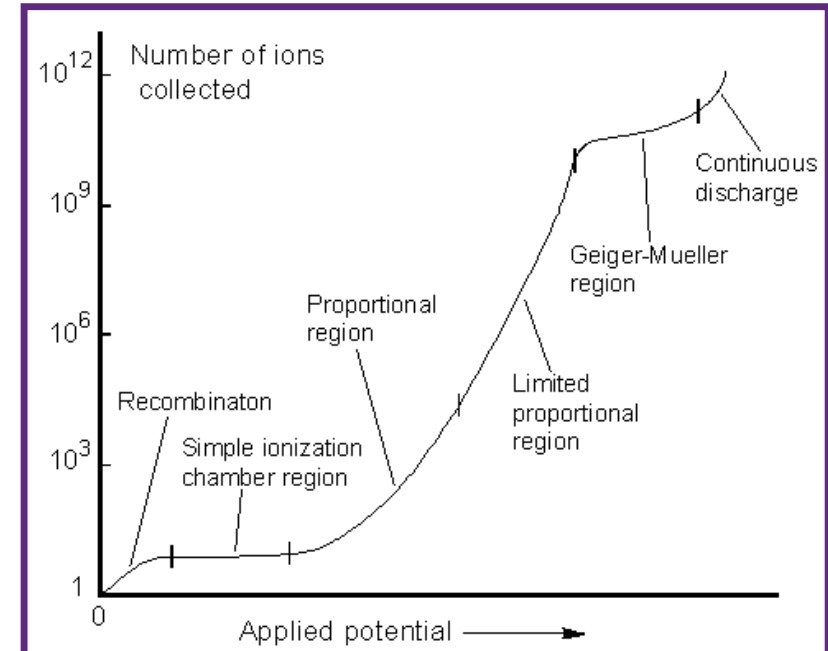
$A > 10^6$  Saturation region: the number of ions collected are independent from the number of primary electrons.

$A > 10^7$  Streamer region: the avalanche develops along the particle track.

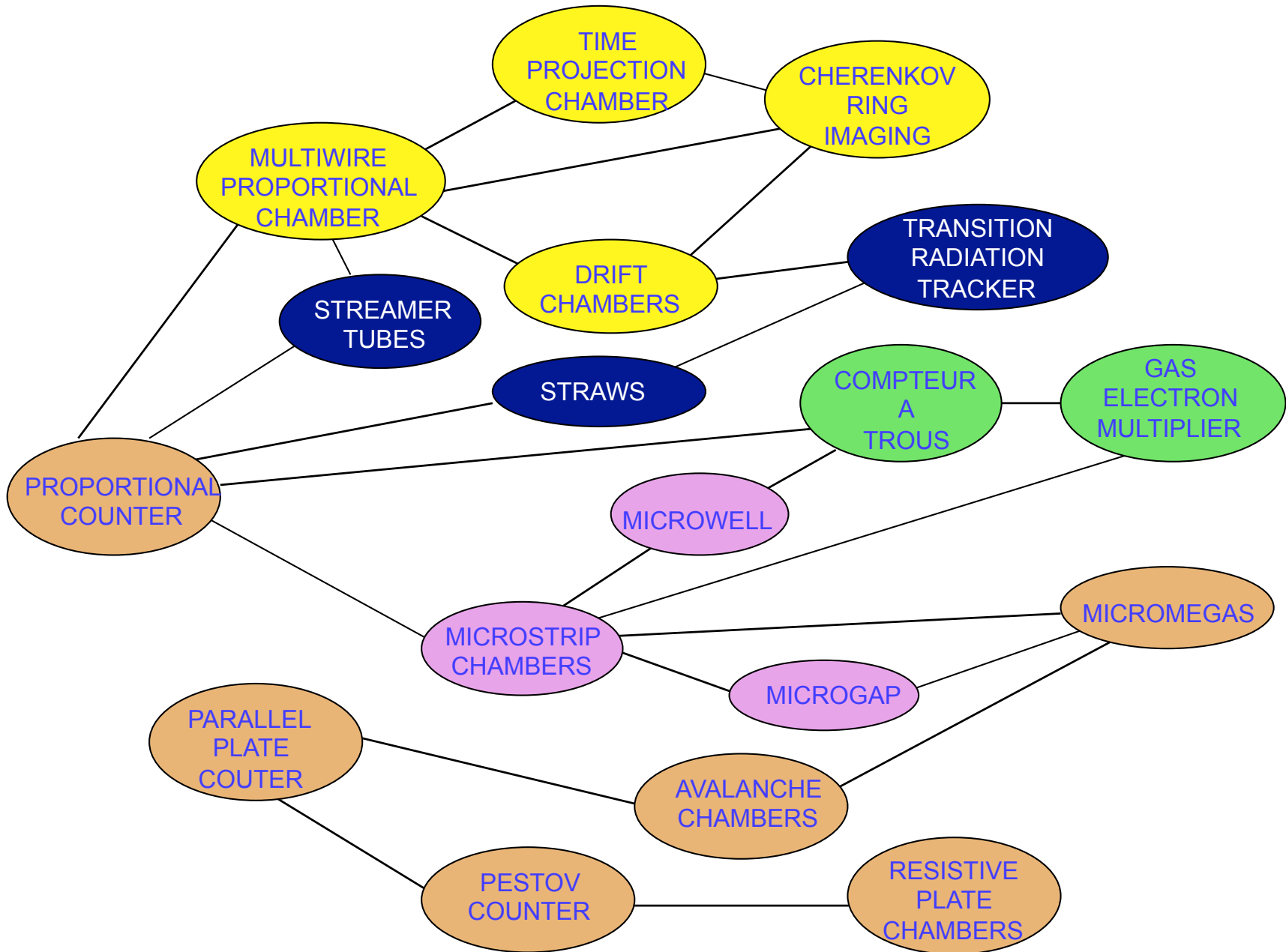
$A > 10^8$  Limited Geiger region: the avalanche is propagated by UV photons.

$A \approx 10^9$  Geiger region: the avalanche is produced along the entire wire.

• • • • Continuous discharge !



# The family of gas detectors



# Multiwire Proportional Chambers

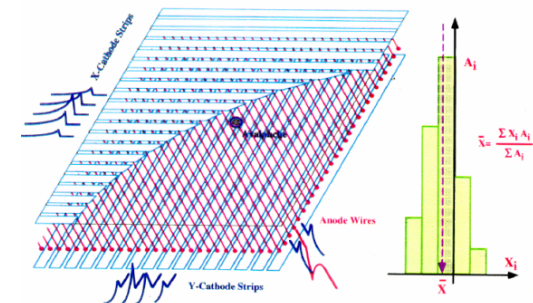
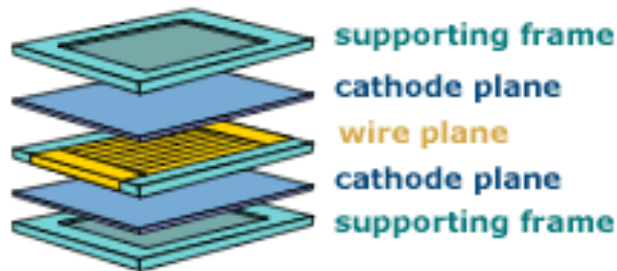
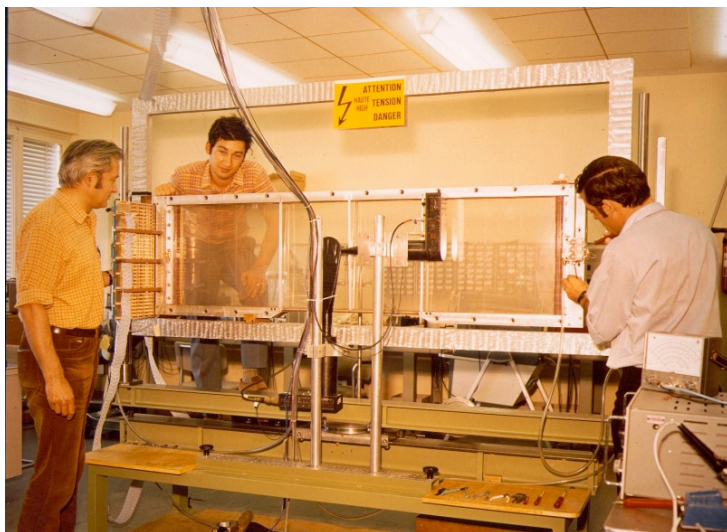
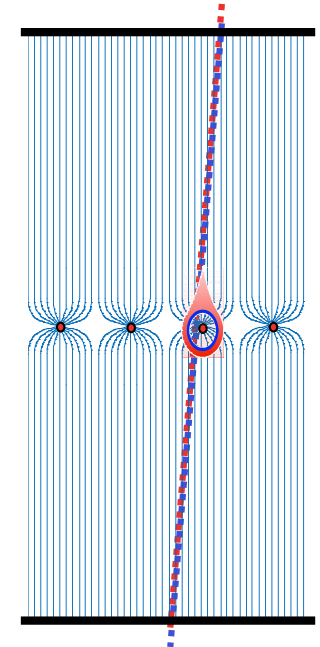
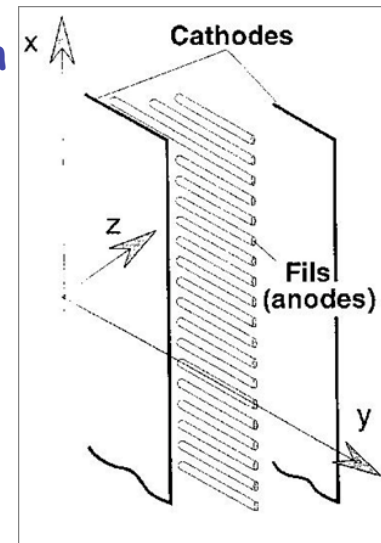
The MWPC was invented by Charpak at CERN

1992



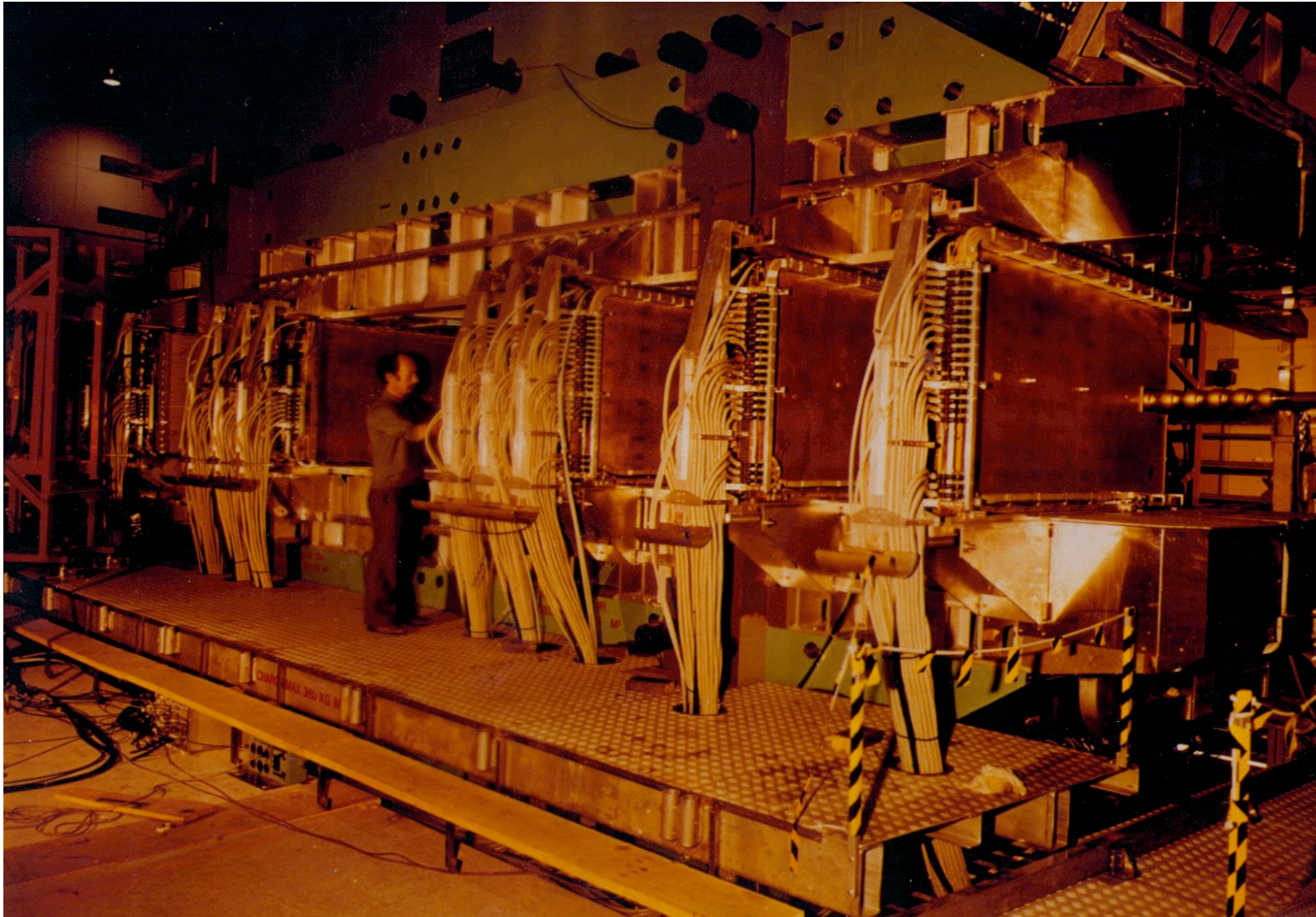
Prize

Principle of proportional counter is extended to large areas. One plane of thin sense wires is placed between two parallel plates. Typical dimensions: wire distance 2-5mm, distance between cathode planes ~10mm. Electrons ( $v \approx 5 \text{ cm}/\mu\text{s}$ ) are collected within  $\approx 100 \text{ ns}$ . The movement of the charges induces a signal on the wire AND on the cathode. By segmentation of the cathode plane and charge interpolation, resolutions of  $50 \mu\text{m}$  can be achieved. Stack several wire planes in different direction to get position location.



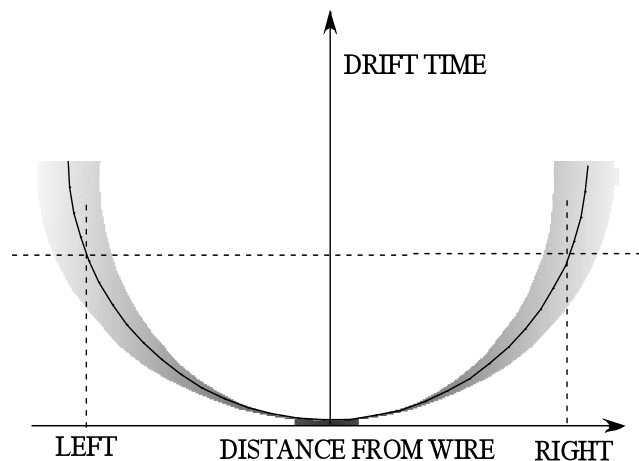
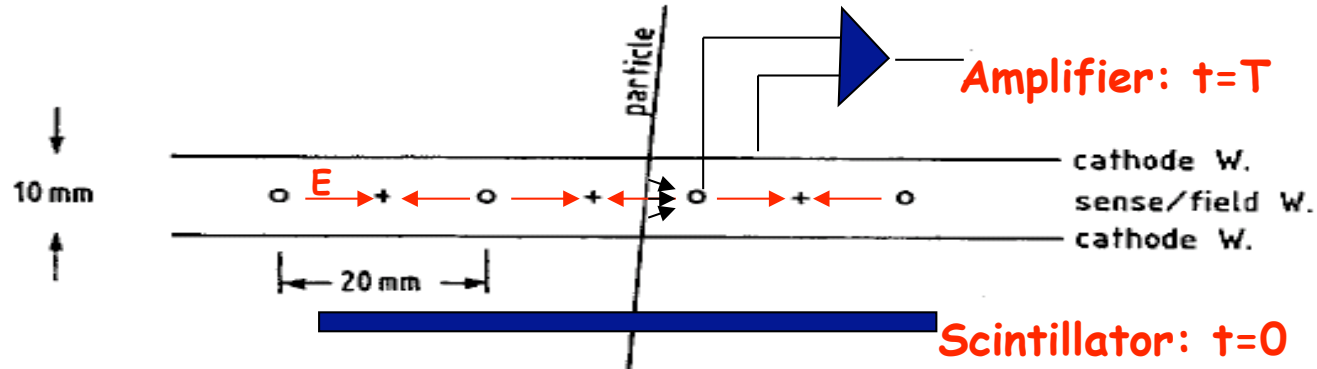
# Lo Split Field Magnet Detector (CERN ISR 1972-1983)

40 large area MWPCs





# Drift Chamber (1971: H. Walenta)

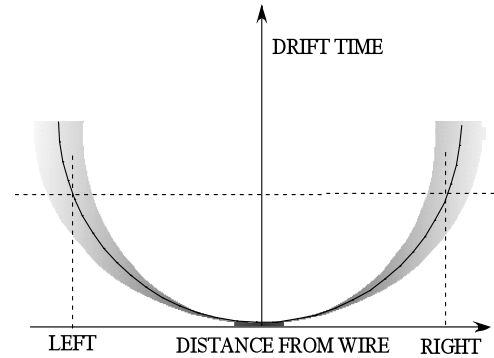
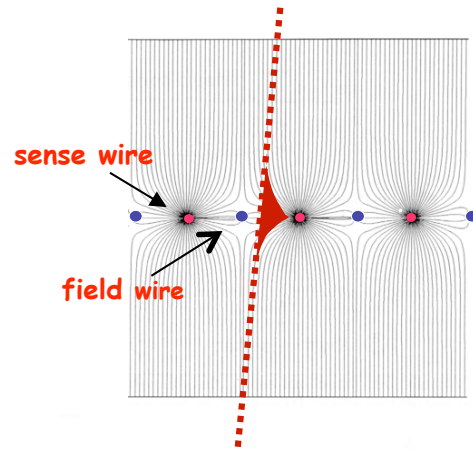


The electric field in an alternating sequence of sense and field wires at different potentials cause the electrons to drift toward the sense wire. The measurement of the drift time  $T$  between the passage of the particle and the arrival of the electrons at the sense wire is a measurement of the position of the particle (precision  $\sim 100\mu\text{m}$ )

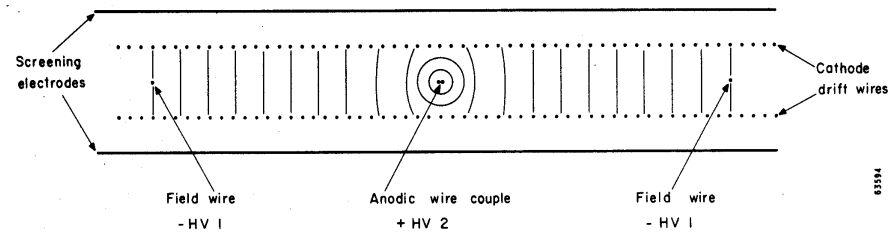
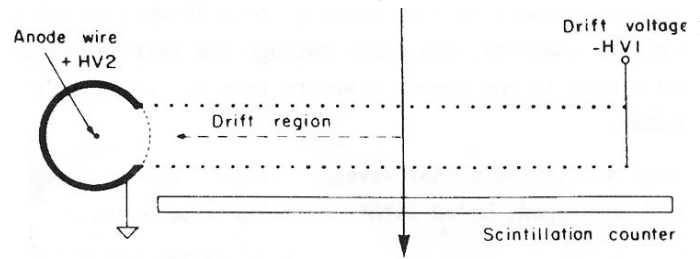
The wire distance can be increased up to several centimeters (drift time  $\sim \mu\text{s}$ ;  $v \approx 5\text{cm}/\mu\text{s}$ ) saving a lot of electronics channels with respect to the MWPC. however:

- Left-Right ambiguity
- Not a linear relation between drift time and distance from the wire

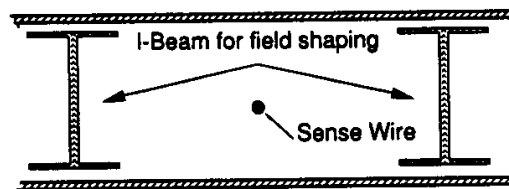
# Drift Chambers



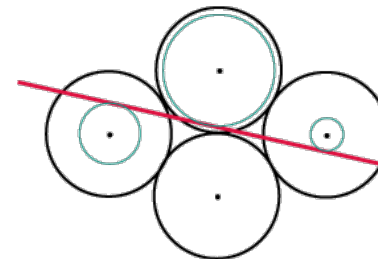
## improved drift cell geometry with constant field



## simplified drift geometry for construction of very large area chambers



DT CMS  
(muon chambers)

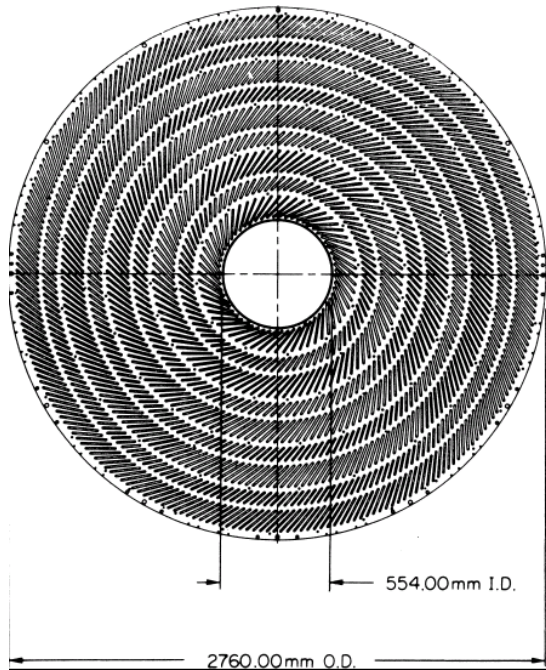


MDT ATLAS  
(muon chambers)

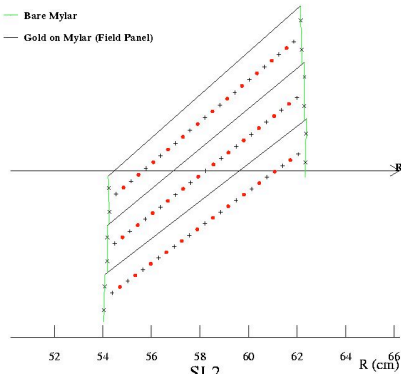
# Drift Chambers

## CDF Central Tracking Chamber

660 drift cells tilted  $45^\circ$  with respect to the particle track to take into account ExB drift!



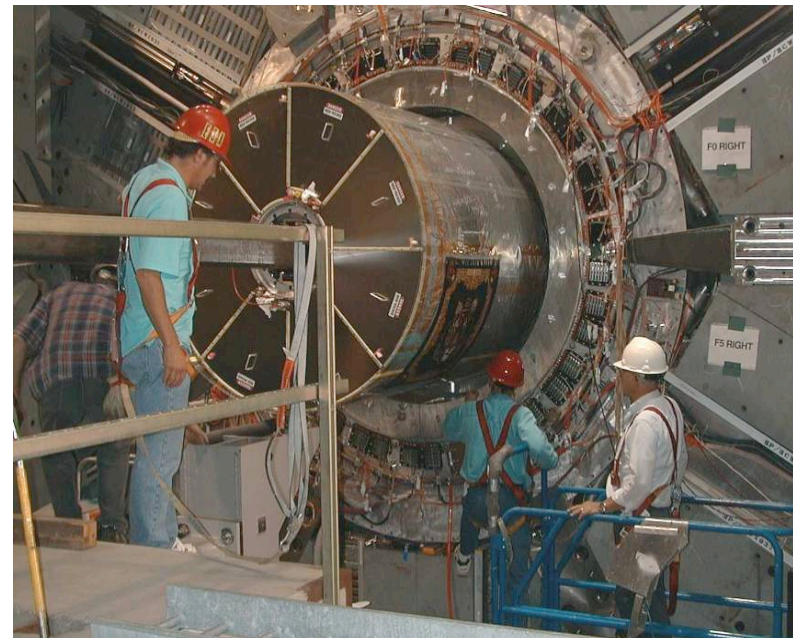
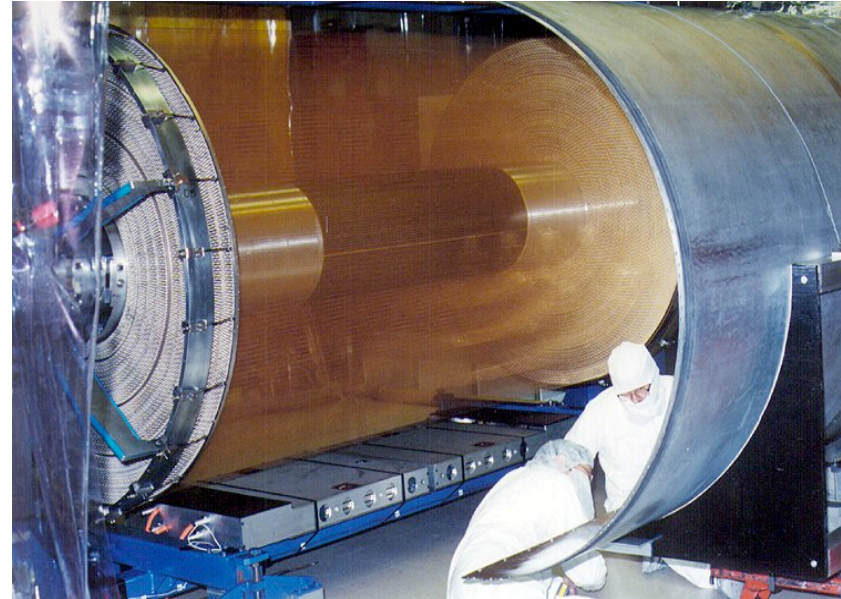
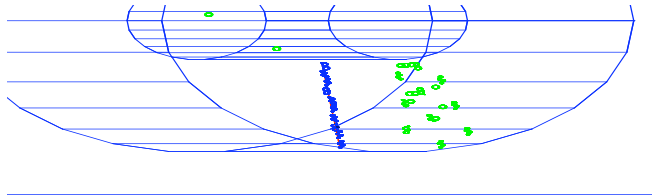
- × Shaper wires
- Bare Mylar
- Gold on Mylar (Field Panel)



# Drift Chambers

## BABAR Central Tracking Chamber

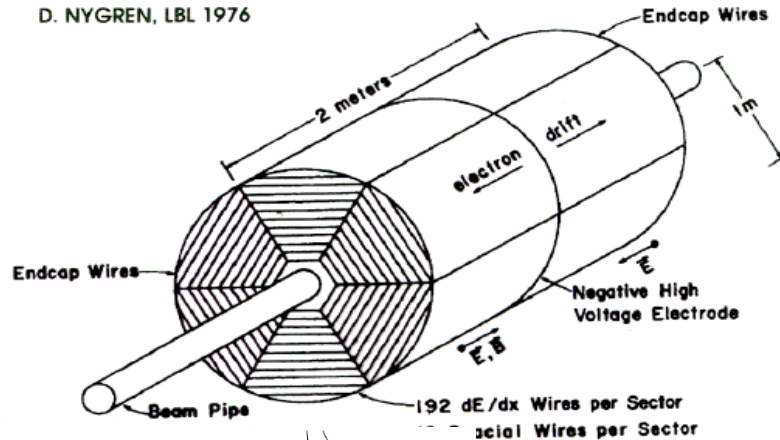
- 2.8 m long
- Gas volume  $\sim 5.6 \text{ m}^3$
- 7100 anode sense wires
- $\sim 50,000$  wires in total



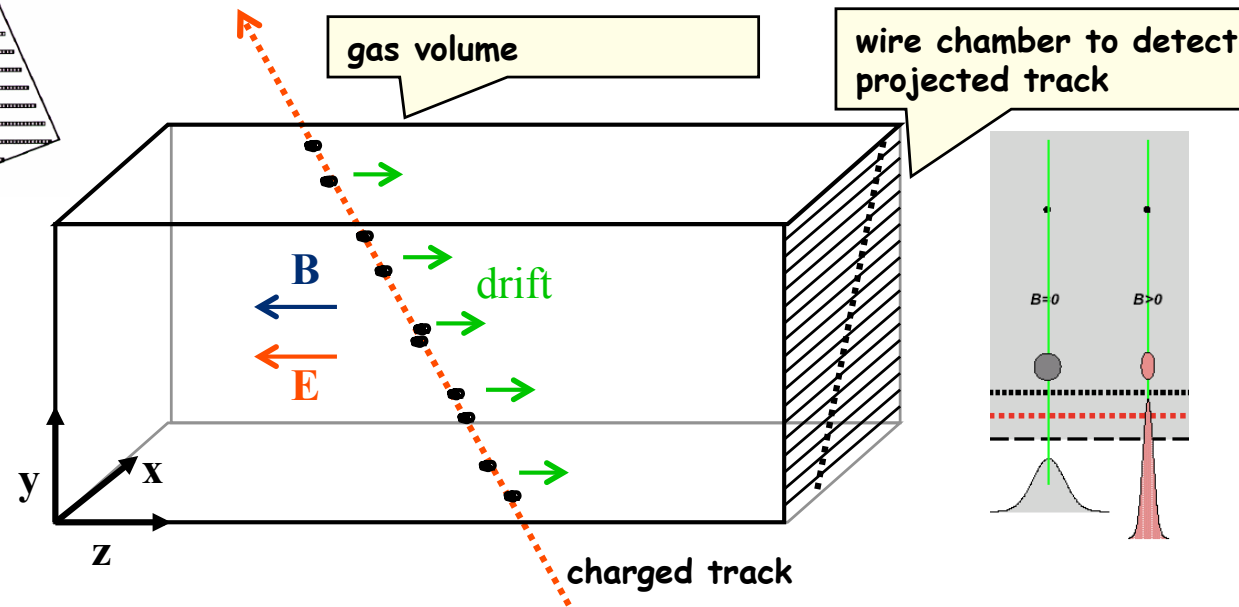
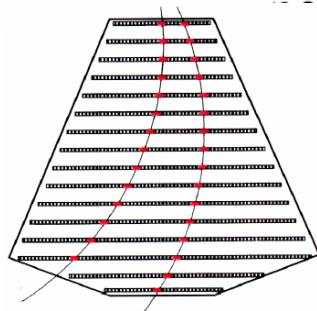
# Time Projection Chamber (TPC)

1976: D. Nygren (LBL)

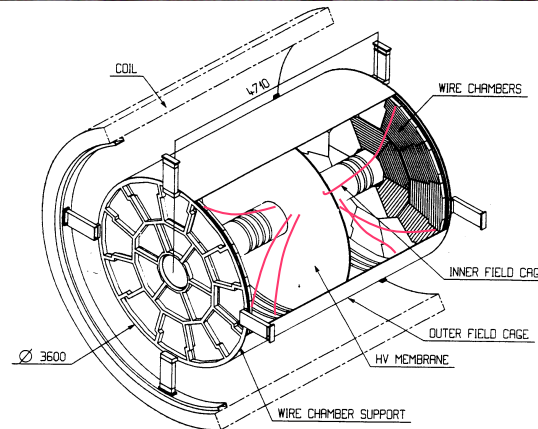
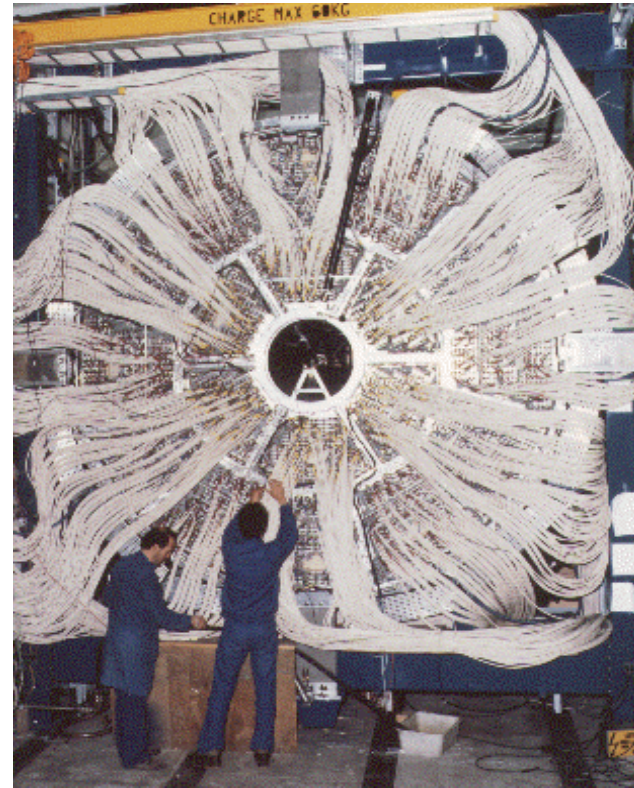
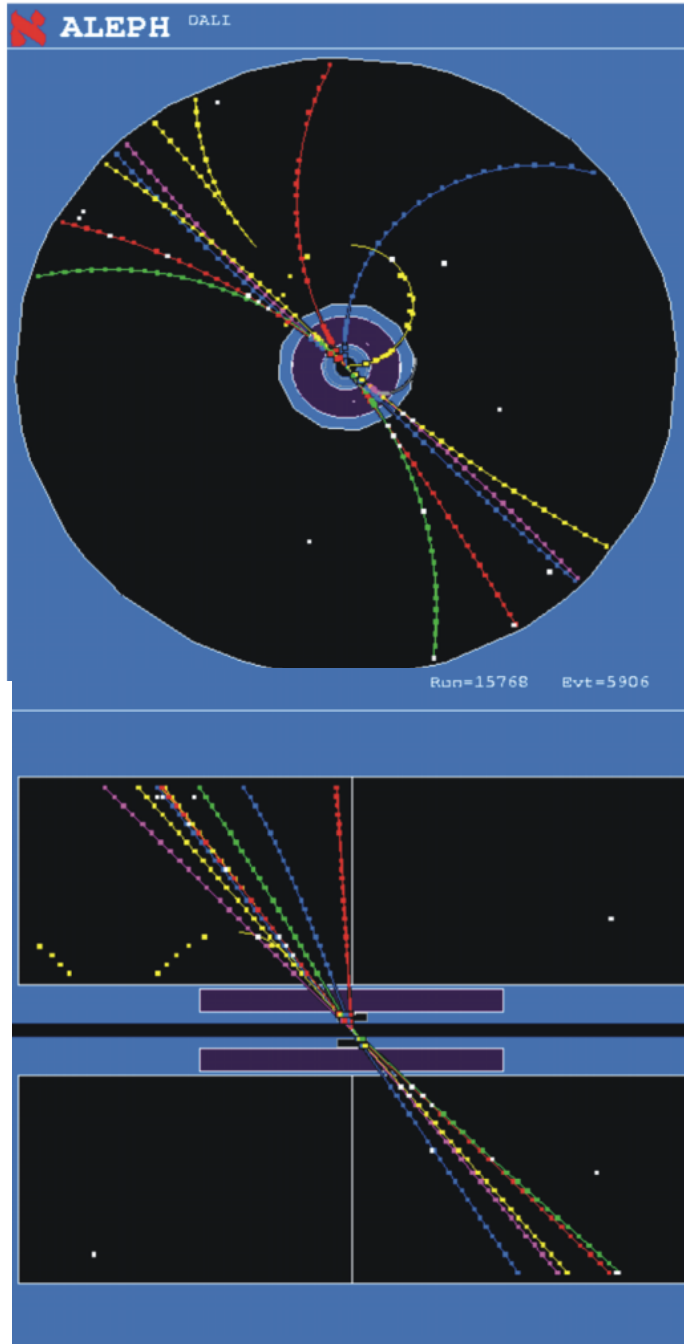
D. NYGREN, LBL 1976



- $E \sim 100\text{-}300 \text{ V/cm}$ . Drift times  $10\text{-}100 \mu\text{s}$
- $B$  for momentum measurement  
(limit electron diffusion up to a factor 5)
- Wire chamber to detect projected tracks.  
Timing gives  $z$  measurement
- Long drift distances up to  $2.5 \text{ m}$



# The ALEPH TPC

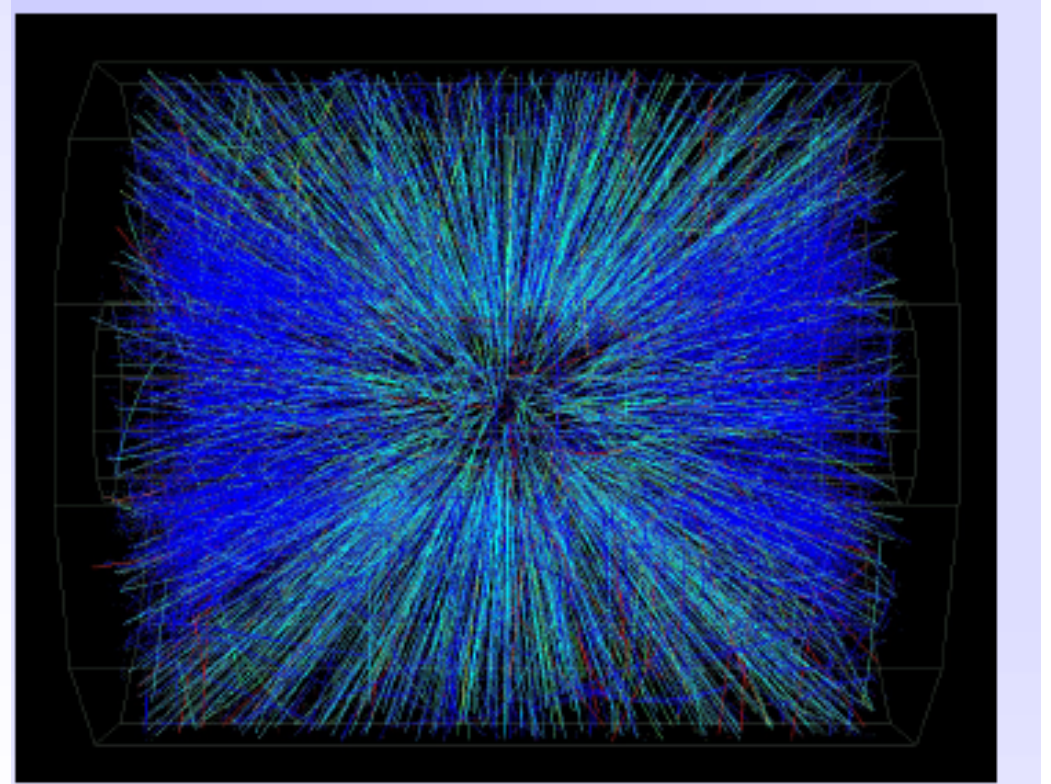
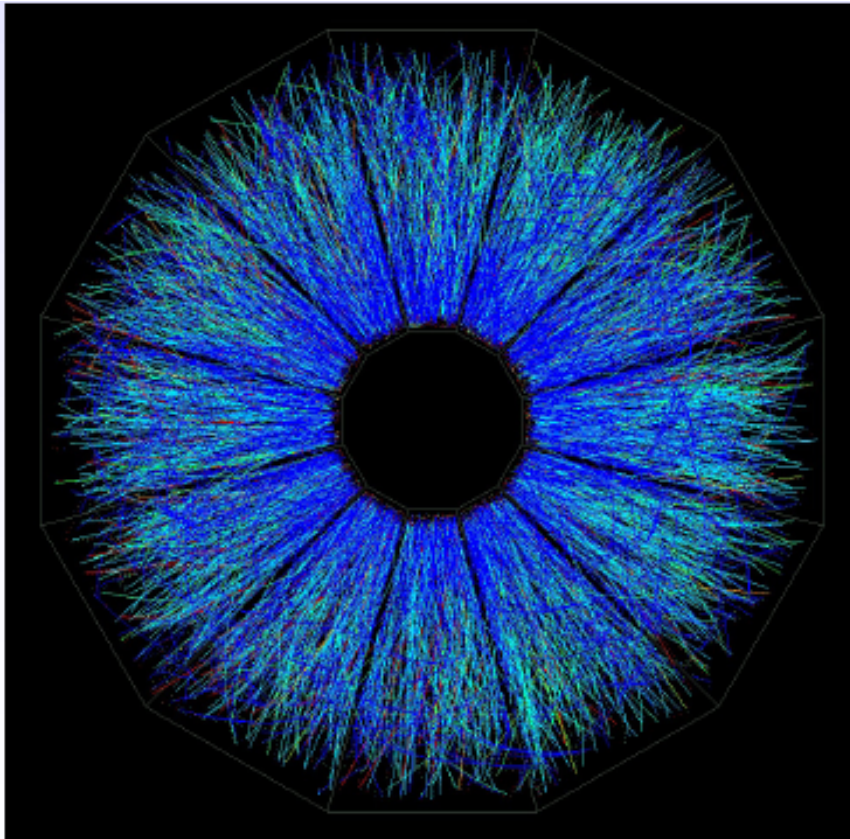


$$\sigma_{R\phi} = 170 \mu\text{m}$$
$$\sigma_z = 740 \mu\text{m}$$

very low multiple scattering in the gas volume of the detector  
→ very good momentum resolution down to low momenta !

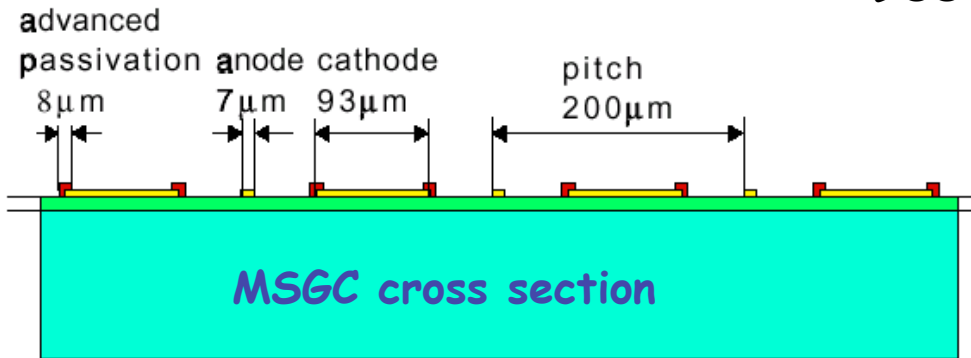
# STAR TPC (BNL)

Event display of a Au-Au collision at CM energy of 130 GeV/n.

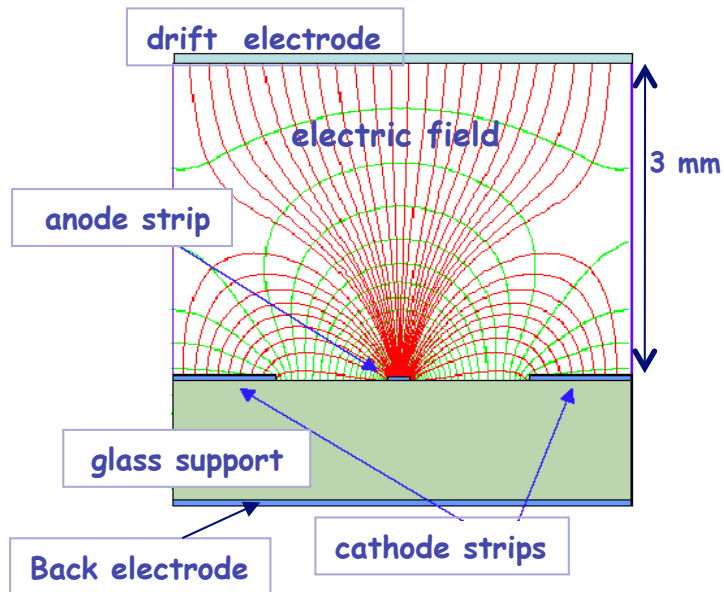
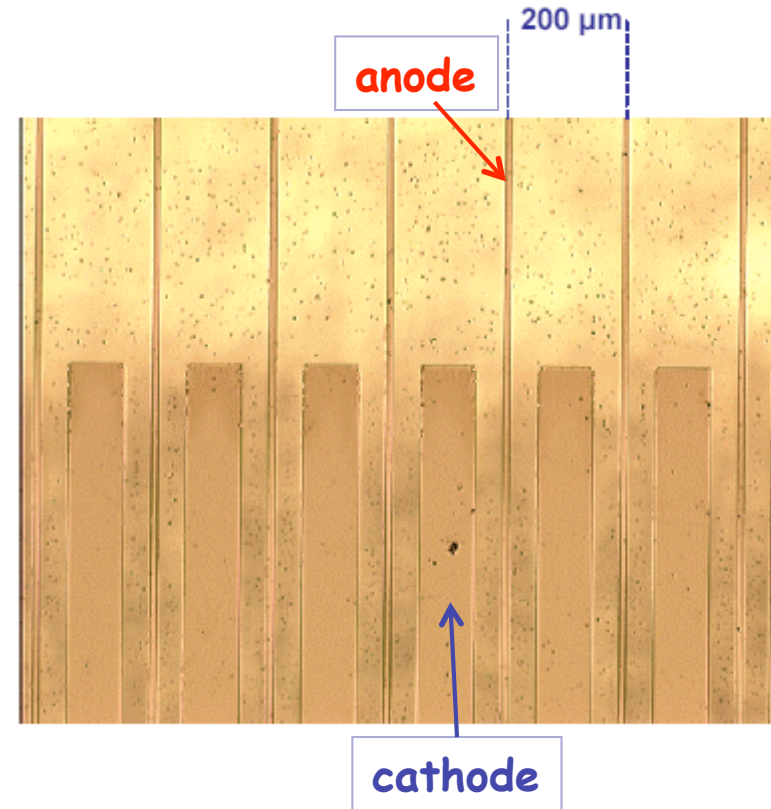


# Micro Strip Gas Chamber

1988: Oed



- advanced passivation: polyimide (2µm)
- metal: gold (0.6-0.8µm)
- undercoating: Pestov or S8900 glass (0.5-1µm)
- substrate: Desag glass (300 µm)

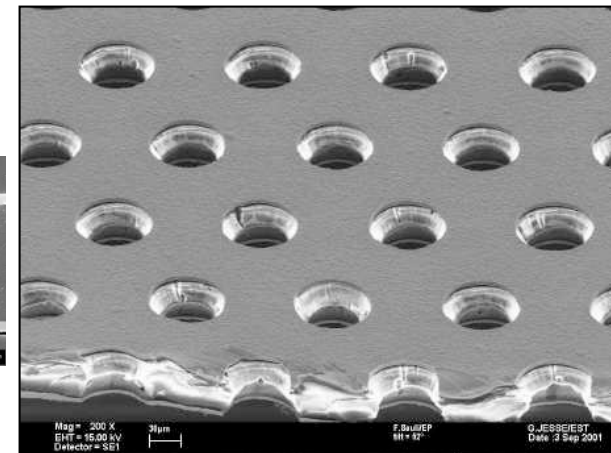
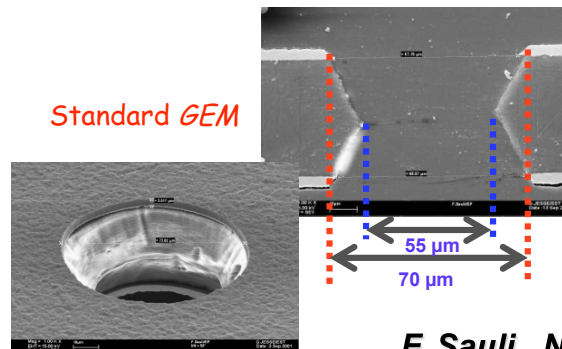
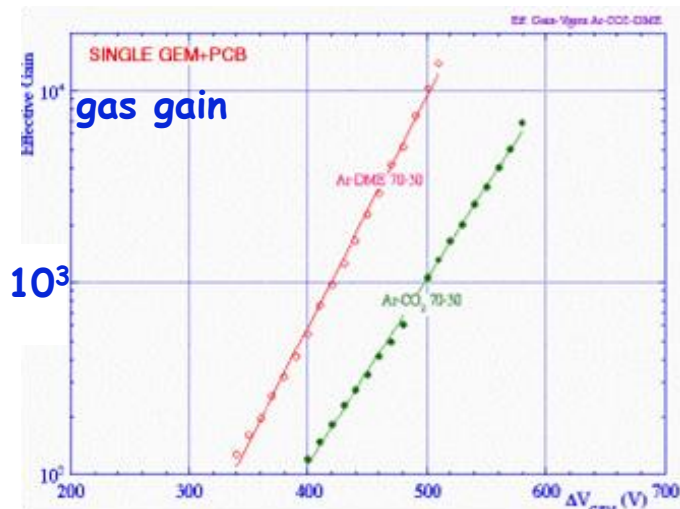
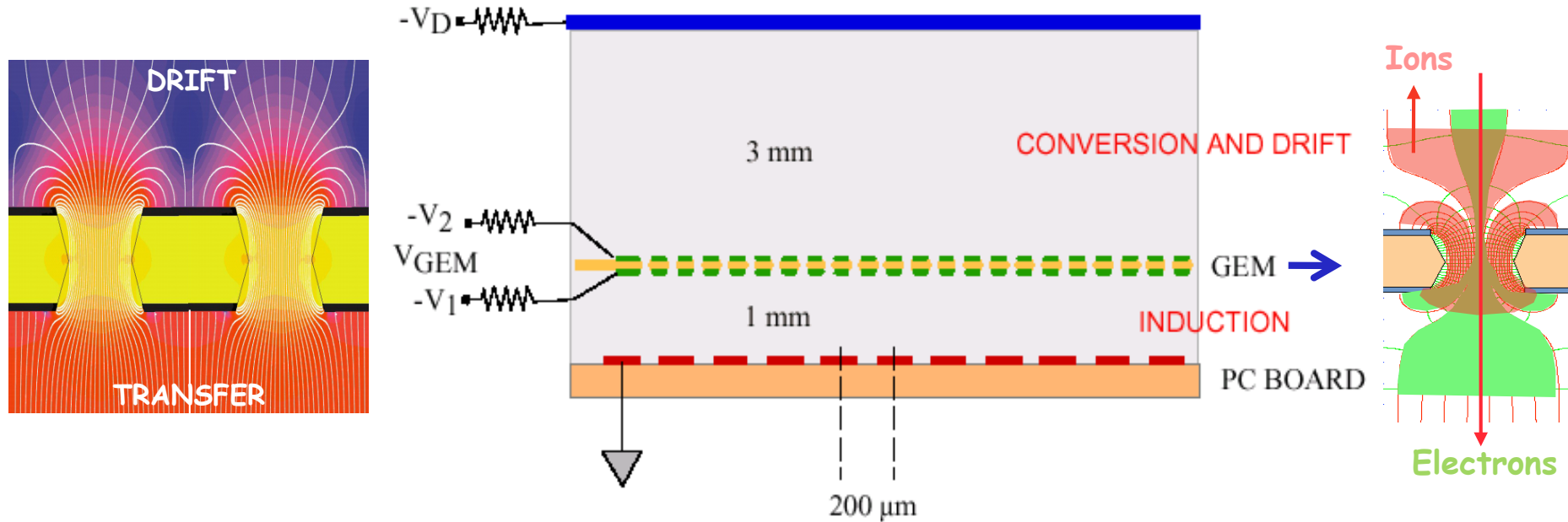


- Signals are much faster than in a MWPC:  
in 50 ns ~70% of the charge is collected !
- Resolution: ~40 µm



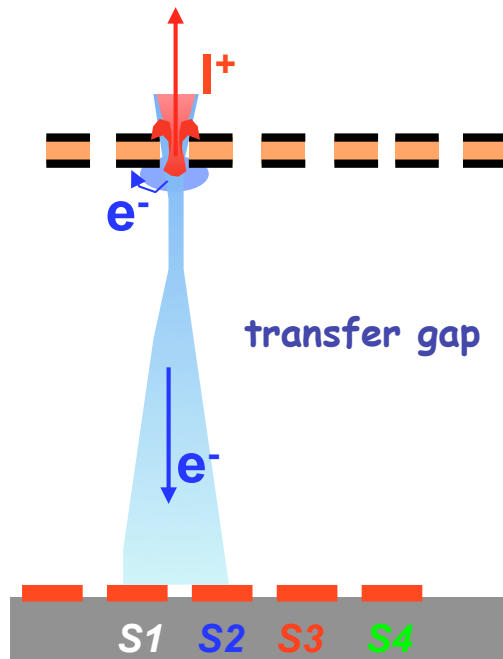
# Gas Electron Multiplier (GEM)

Thin Kapton foil (50  $\mu\text{m}$ ) double side metal-coated (Cu 5  $\mu\text{m}$ )  
70  $\mu\text{m}$  holes at 140  $\mu\text{m}$  pitch

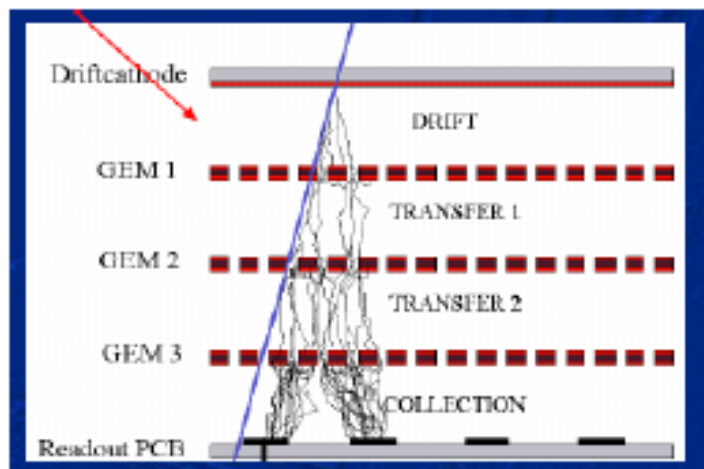
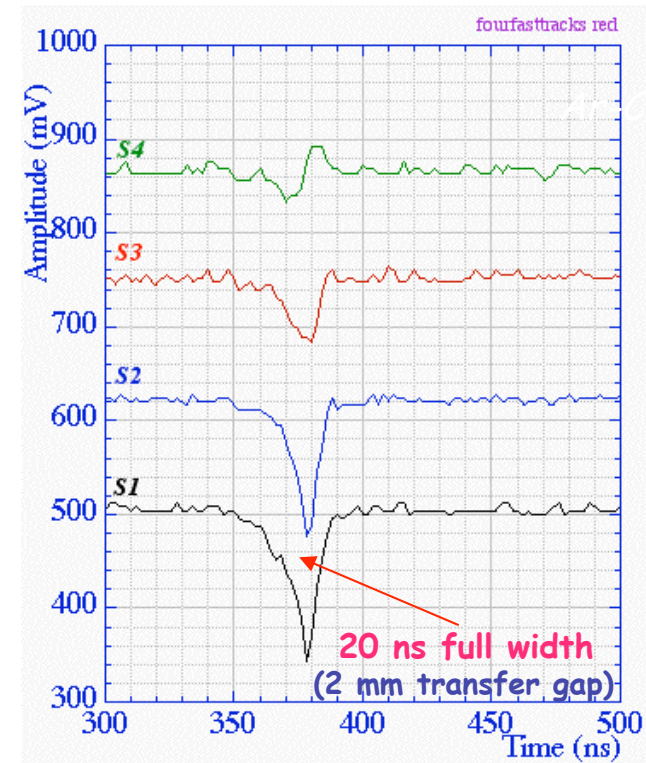


F. Sauli, Nucl. Instr. and Methods A386(1997)531

# Gas Electron Multiplier (GEM)

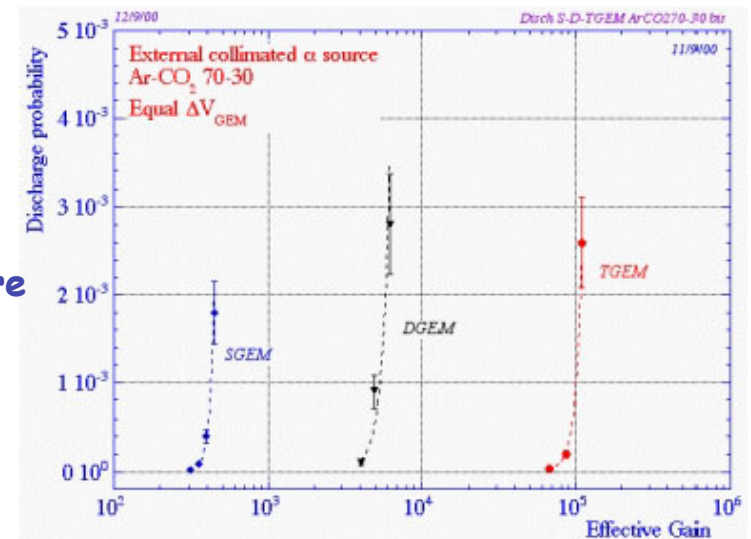


Only electrons are drifting in the transfer gap towards the readout electrodes:  
 ⇒ no ion long tail  
 ⇒ very fast signal  
 ⇒ very good time resolution



Triple GEM

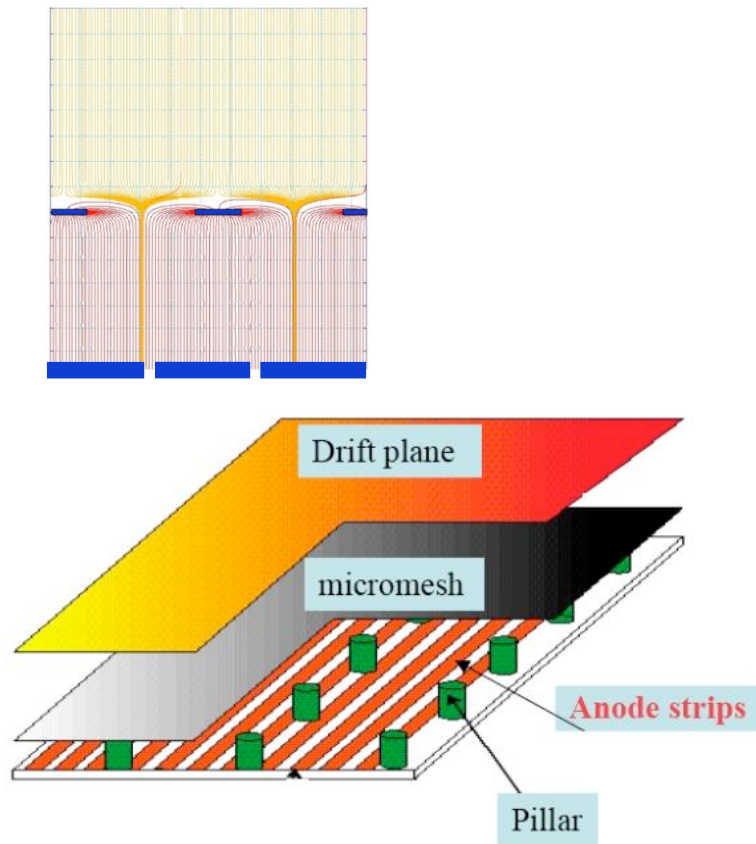
Higher final gas gains can be obtained with a series of GEMs in cascade to reduce the gain/stage and therefore reducing the discharge probability



# Other kinds of Micro Pattern Gas Detectors

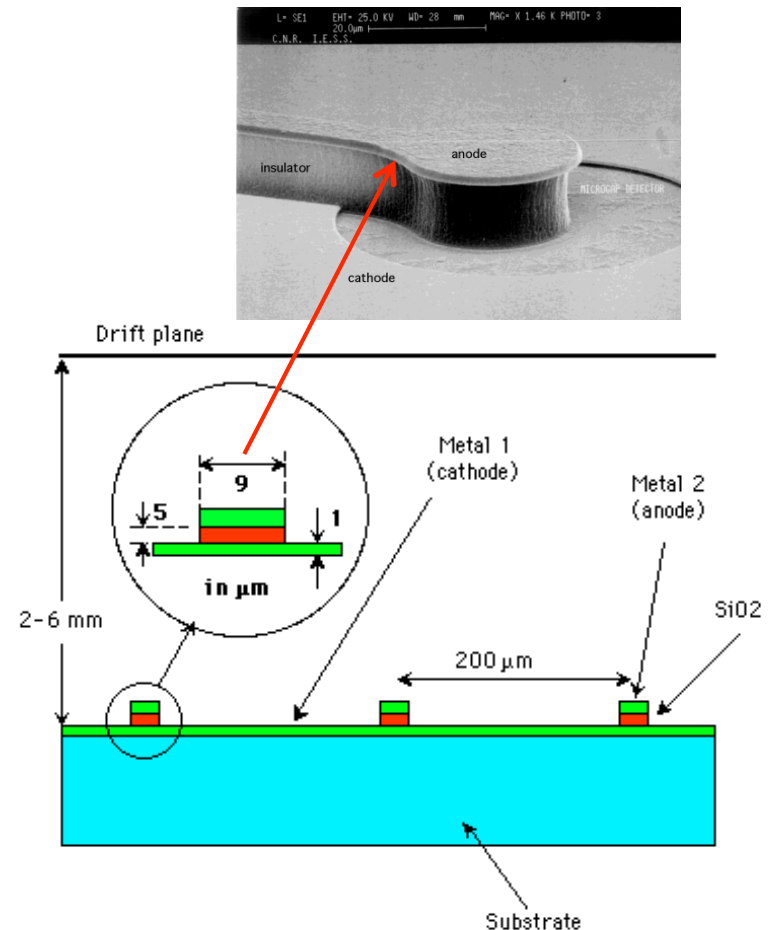
Several different geometries of micro pattern gas detectors have proven to work efficiently at high rate: a couple of examples

## MICROMEAS



Y. Giomataris et al, Nucl. Instr. and Meth. A376(1996)239

## MicroGap chamber (MGC)

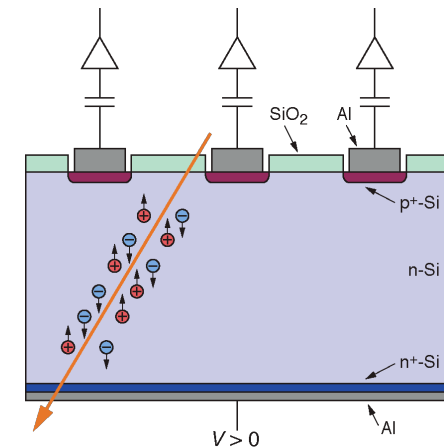


R. Bellazzini et al., Nucl. Instr. Meth. A335 (1993) 69

# Solid State Detectors

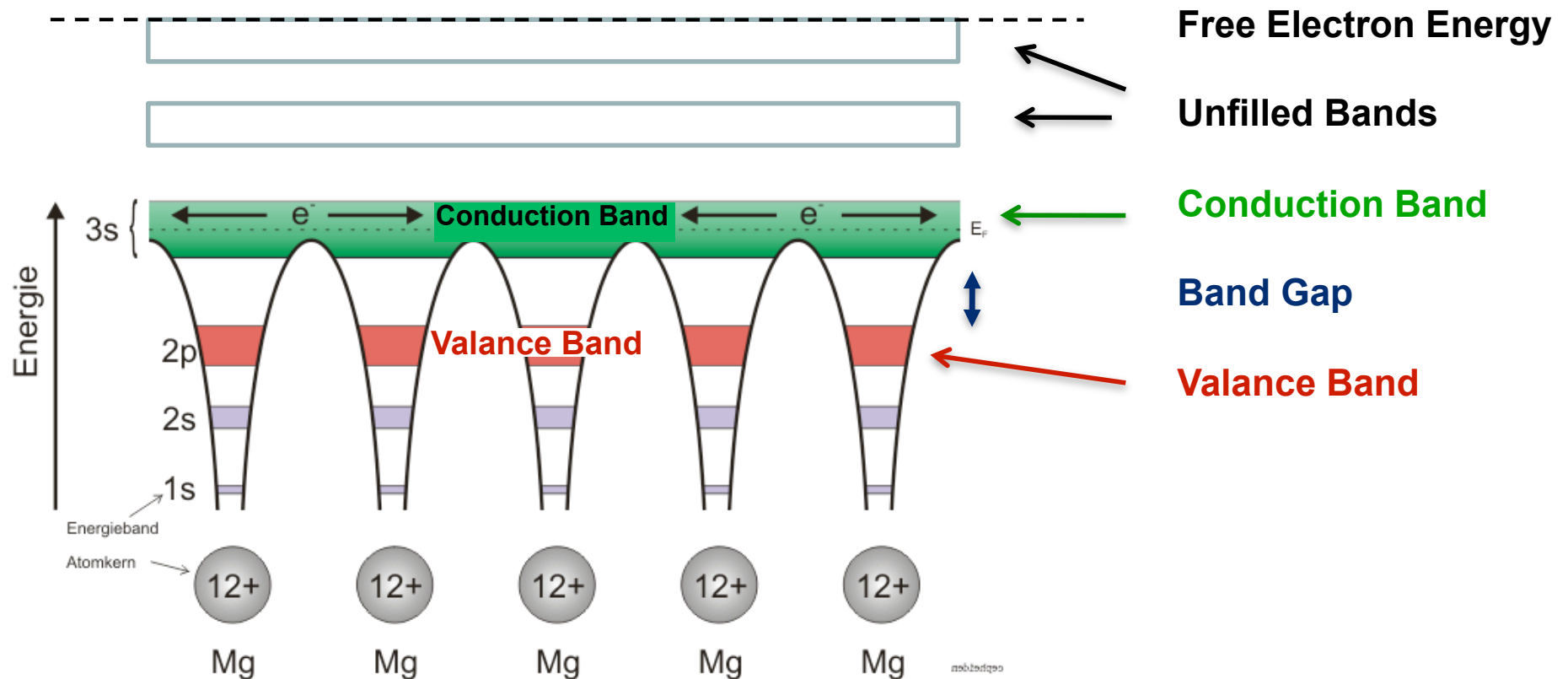
In solid state detectors the charges produced by the ionization due to the incoming particle are sufficient to provide a measurable signal.

- ❑ Solid state detectors have a high density
  - large energy loss in a short distance:  
116 (78) keV = mean (most probable) energy loss for 300 $\mu$ m Silicon thickness
- ❑ Low ionisation energy (few eV per e-hole pair) compared to gas detectors (20-40 eV per e-ion pair)
  - 3.6 eV for silicon to create an e-hole pair
  - ⇒ 72 e-h/ $\mu$ m (most probable); 108 e-h/ $\mu$ m (mean)
  - ⇒ most probable charge 300 $\mu$ m Silicon thickness:  
 $\approx 21600 e \quad \approx 3.6 fC$
- ❑ Drift velocity much faster than in gas detectors:
  - Very fast signals of only a few ns length !
- ❑ Diffusion effect is smaller than in gas detectors:
  - achievable position resolution of less than 10  $\mu$ m



# Solid State Detectors

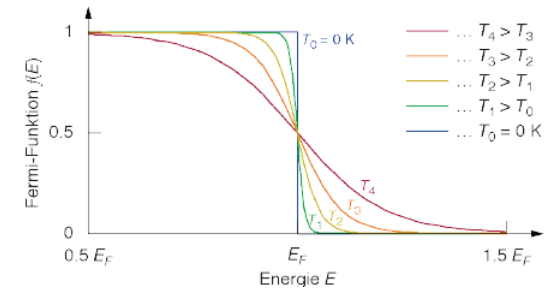
In an isolated atom of a gaseous detector the electrons have only discrete energy levels and when are liberated from the atoms by an ionizing particle they (and the ions) can freely move under an applied electric field. In solid state (crystal) material the atomic levels merge to energy bands. Inner shell electrons, in the lower energy bands, are closely bound to the individual atoms. However electrons in the **conduction band** and the holes in the lower **valence band** (bands that are still bound states of the crystal, but they belong to the entire crystal) can freely move around the crystal, if an electric field is applied.



# Solid State Detectors

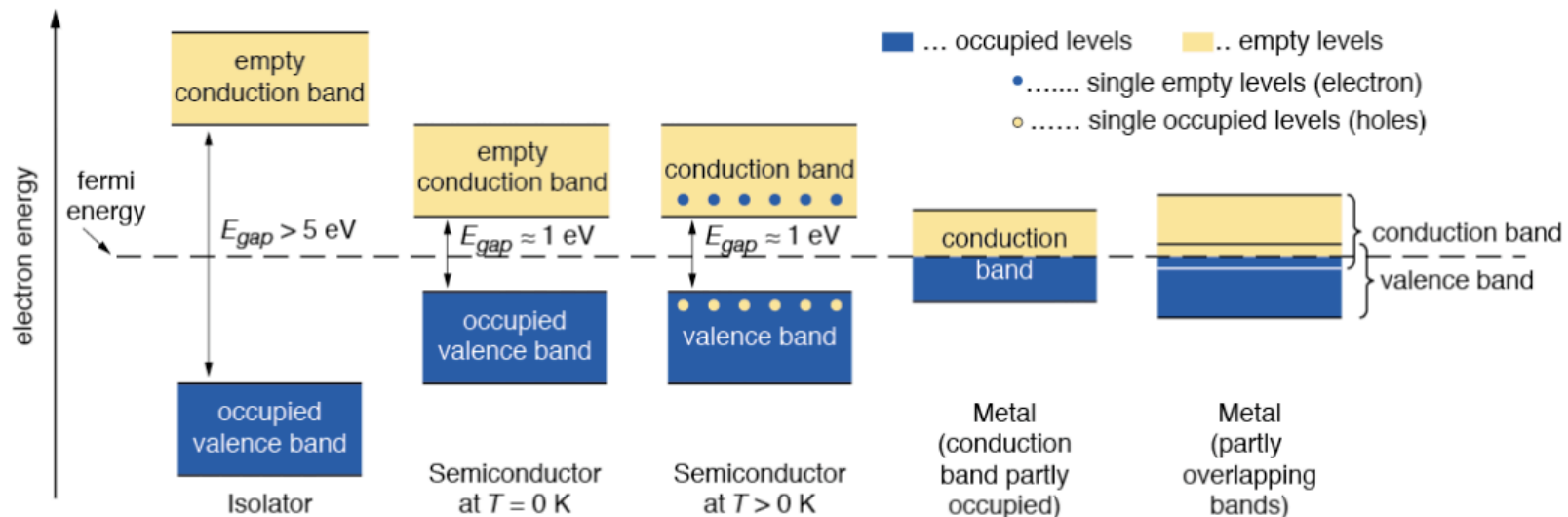
Fermi distribution  $f(E)$  describes the probability that an electronic state with energy  $E$  is occupied by an electron:

$$f(E) = \frac{1}{1 + e^{\frac{E - E_F}{kT}}}$$



The Fermi level  $E_F$  is the energy at which the probability of occupation is 50%. For metals  $E_F$  is in the conduction band, for semiconductors and isolators  $E_F$  is in the band gap.

In metals the conduction and the valence band partially overlap, whereas in isolators and semiconductors these levels are separated by an energy gap. This energy gap  $E_g$  is called band gap. In isolators this gap is large.

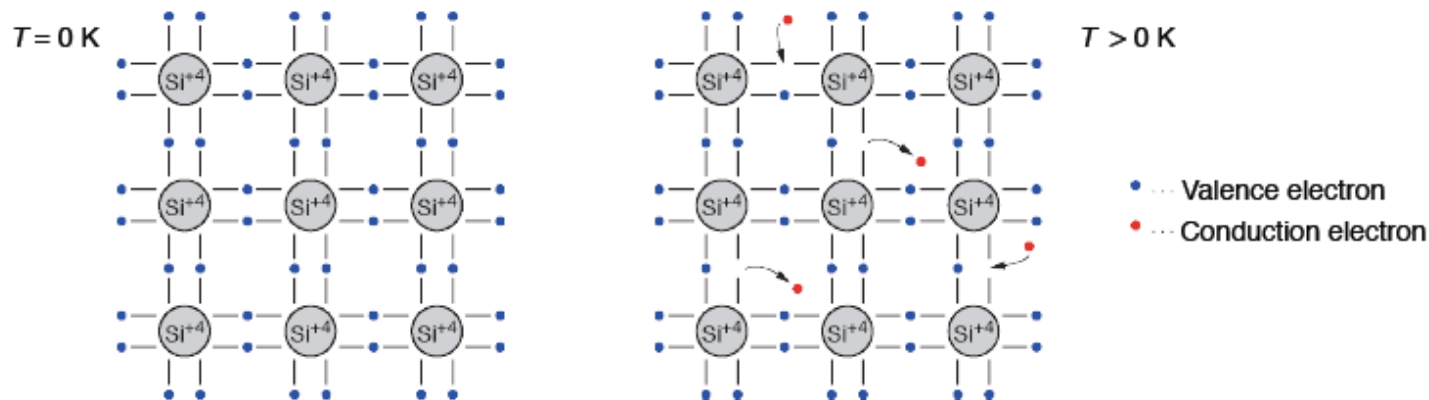


# Solid State Detectors

- ❖ The energy gap  $E_g$  (band gap) of Diamond/Silicon/Germanium is 5.5,1.12,0.66 eV
- ❖ Due to the small band gap, electrons already occupy the conduction band gap in many semiconductors at room temperature.
- ❖ Electrons from the conduction band may recombine with holes
- ❖ The thermal excitation excites electrons into the conduction band leaving a hole in the valence band. Thermal equilibrium is reached at intrinsic carrier concentration:

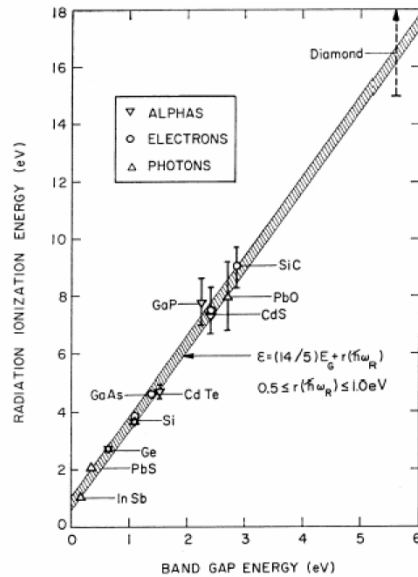
$$n_i = n_e = n_h \propto T^{\frac{3}{2}} \cdot \exp\left(-\frac{E_g}{2kT}\right)$$

- ❖ Therefore the number of electrons in the conduction band, and thus also the conductivity of the semiconductor, increases with temperature.



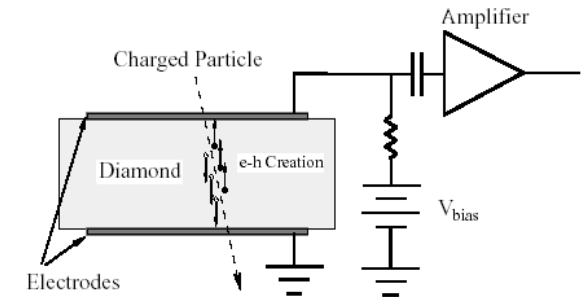
In silicon at room temperature the intrinsic carrier concentration is  $1.45 \cdot 10^{10} \text{ cm}^{-3}$ . With approximately  $10^{22} \text{ Atoms/cm}^3$  about 1 in  $10^{12}$  silicon atoms is ionised. This yields an intrinsic resistivity of:  $\rho \approx 230 \text{ k}\Omega \text{ cm}$

# Solid State Detectors



	Diamond	Silicon	Germanium
Band gap $E_g$ [eV]	5.5	1.12	0.66
Energy $E_{e/h}$ for e-h pair [eV]	13	3.6	2.9
Density [g/cm <sup>3</sup> ]	3.51	2.33	5.32
e-mobility $\mu_e$ [cm <sup>2</sup> /Vs]	1800	1450	3900
h-mobility $\mu_h$ [cm <sup>2</sup> /Vs]	1200	450	1900
Intrinsic charge carrier: $n_i$ [cm <sup>-3</sup> ] (T=300 K)	$\approx 10^{-27}$	$1.45 \cdot 10^{10}$	$2.4 \cdot 10^{13}$

In Diamond detectors there are very few charge carriers at room temperature ( $n_i[\text{cm}^{-3}] \approx 10^{-27}$ ) due to large band gap while many e-h pairs are produced by an ionizing particle



In a 300 $\mu\text{m}$  Silicon detector the number (mean) of e-h pairs produced by the passage of a charged particle at the minimum ionizing is given by:

$$n_{e/h} = dE/dx \cdot d / E_{e/h} = 3.87 \cdot 10^6 \text{ eV/cm} \cdot 0.03 \text{ cm} / 3.6 \text{ eV} \approx 3.2 \cdot 10^4 \text{ e-h pairs}$$

In the same detector of an area  $A=1\text{cm}^2$  the intrinsic charge carrier (T=300 K) is:

$$n_i \cdot d \cdot A = 1.45 \cdot 10^{10} \text{ cm}^{-3} \cdot 0.03 \text{ cm} \cdot 1 \text{ cm}^2 \approx 4.35 \cdot 10^8 \text{ e-h pairs}$$

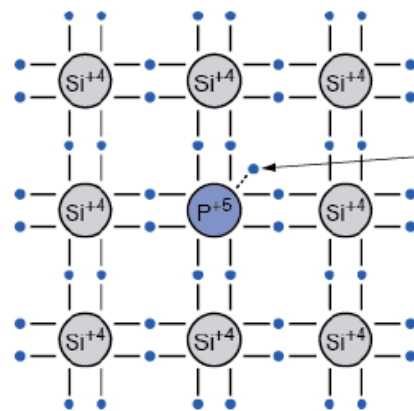
In silicon the thermal e-h pairs are four orders of magnitude larger than signal !!!

→ remove the charge carrier !

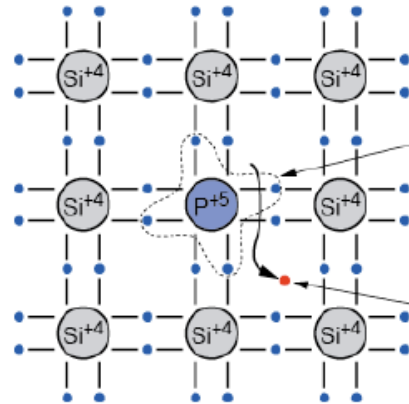


# n-Doping in Silicon

Doping with an element +5 atom with one valence electron more than silicon (e.g. P, As ). The 5th valence electrons is weakly bound. The doping atom is called donor. The n-doped silicon becomes a n-type conductor (more electrons than holes)



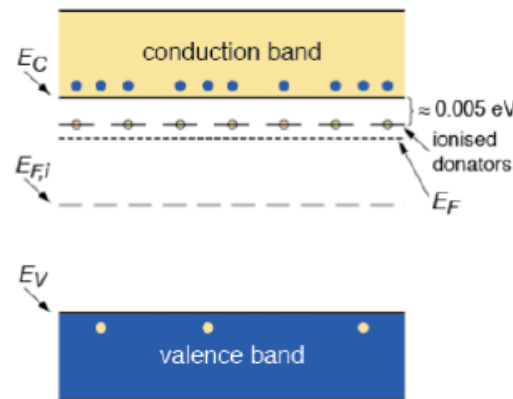
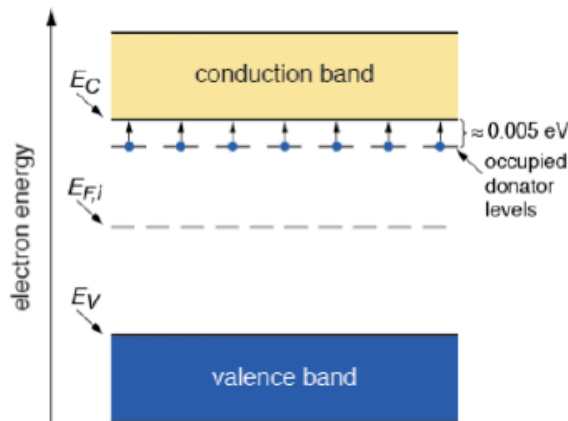
weakly bound electron



positive ion

conduction electron

Typical doping concentrations for Si detectors are  $\approx 10^{12}$  atoms/cm<sup>3</sup>



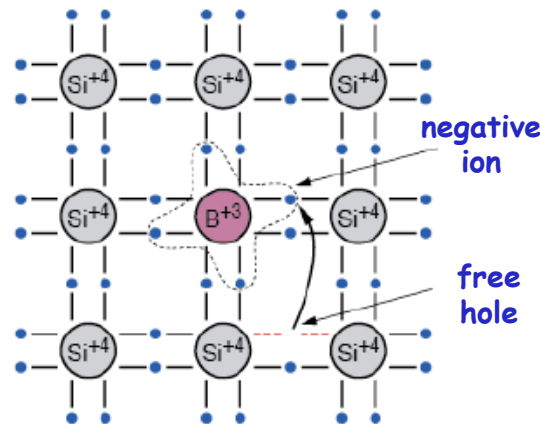
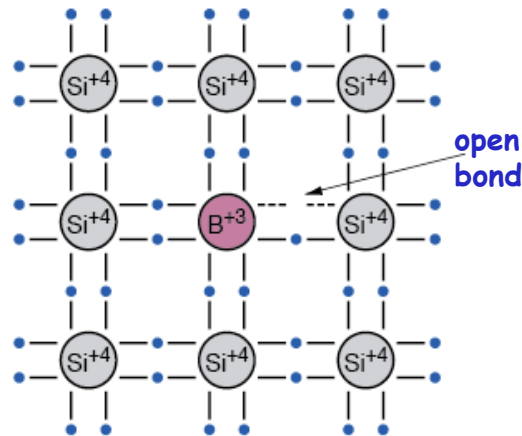
The energy level of the donor is just below the edge of the conduction band. At room temperature most electrons are raised to the conduction band. The Fermi level  $E_F$  moves up.

■ ... empty levels  
■ ... occupied levels

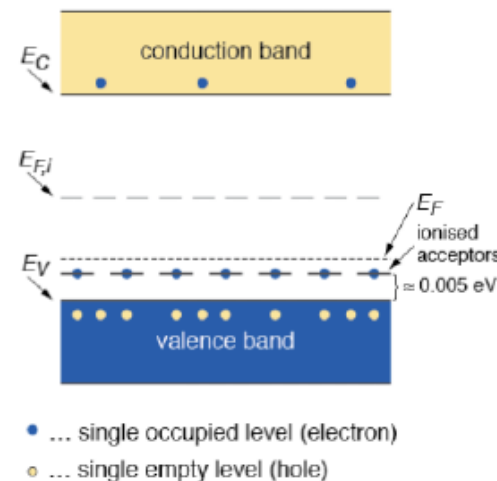
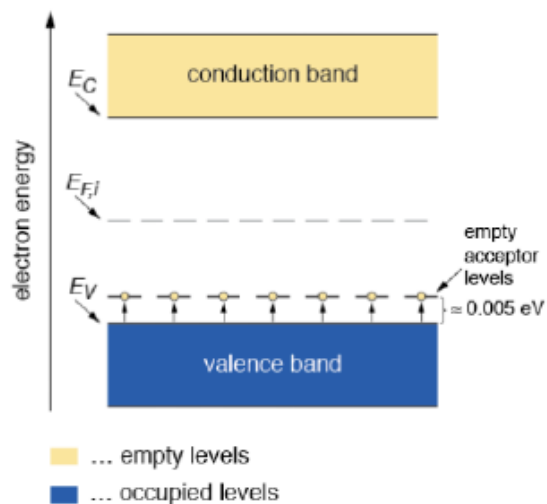
● ... single occupied level (electron)  
○ ... single empty level (hole)

# p-Doping in Silicon

Doping with an element +3 atom with one valence electron less than silicon (e.g. B, Ga). One valence bond remains open and attracts electrons from the neighbor atoms. The doping atom is called acceptor. The p-doped silicon becomes a p-type conductor (more holes than electrons)



Typical doping concentrations for Si detectors are  $\approx 10^{12}$  atoms/cm<sup>3</sup>

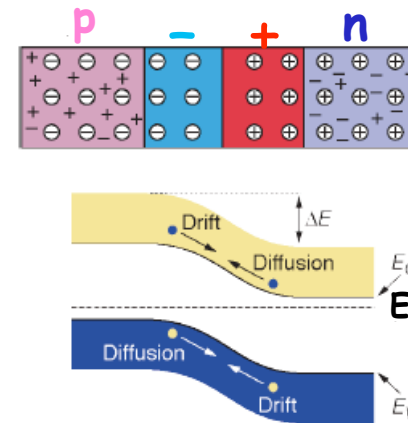
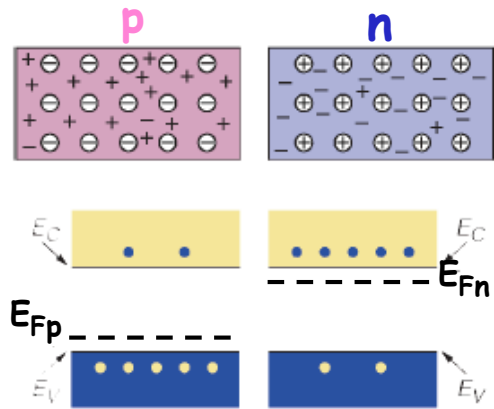


The energy level of the acceptor is just above the edge of the valence band. At room temperature most levels are occupied by electrons leaving holes in the valence band. The Fermi level  $E_F$  moves down.

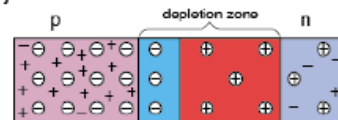
# Si-Diode as Si-Detector

At the p-n junction the difference in the fermi levels cause diffusion of charge carries until thermal equilibrium is reached and the electric field thus created stops further diffusion. At this point the fermi level is equal.

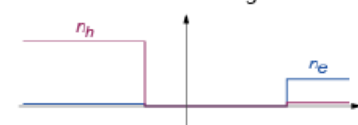
A zone free of charge carries, called **depletion region**, is thus established .



pn junction scheme

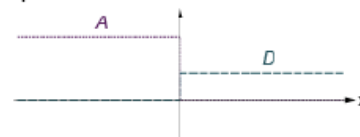


concentration of free charge carriers

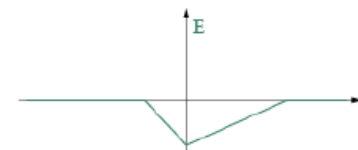


- + hole      ○ acceptor
- electron      ○ donator

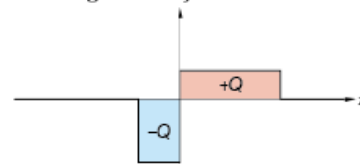
acceptor and donator concentration



electric field



space charge density



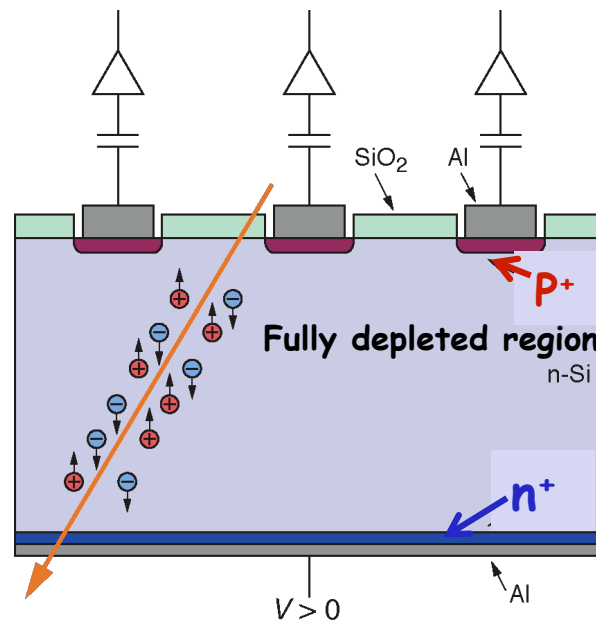
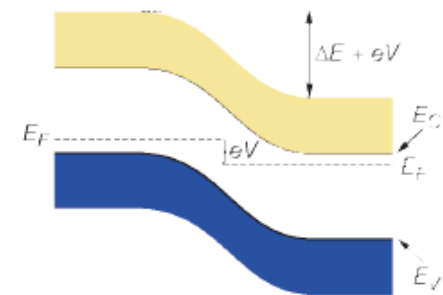
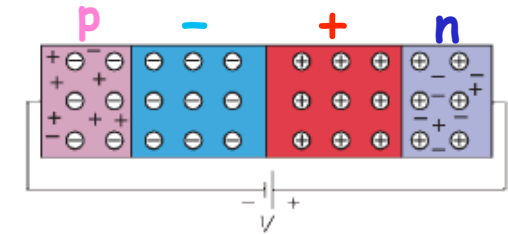
electric potential



# Si-Diode as Si-Detector

By applying an external voltage  $V$ , the depletion zone can be extended to the entire diode.

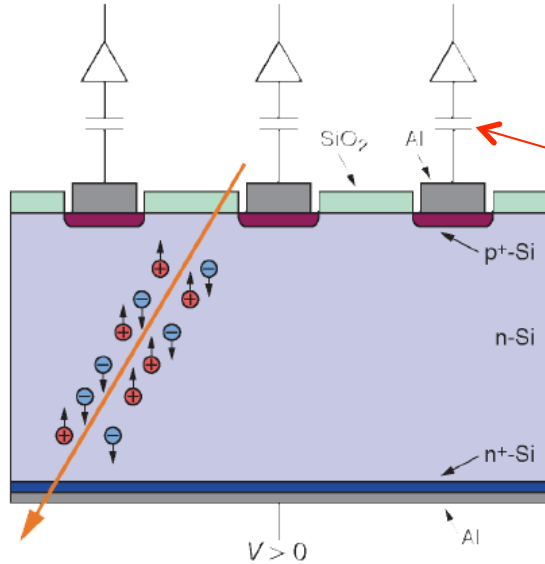
An incoming particle can then produce by ionization free charge carriers in the diode. The charges carriers drift in the electric field and induce an electrical signal on the electrodes.



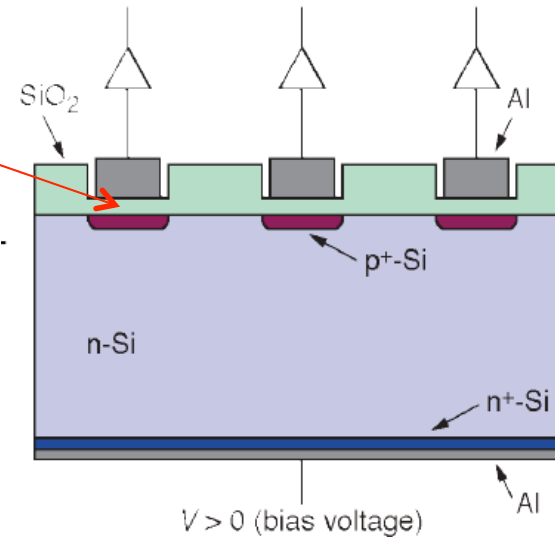
→ That is the way a Silicon detector can work !

# Detector Structures

DC coupled strip detector



AC coupled strip detector



A typical n-type Si strip detector:

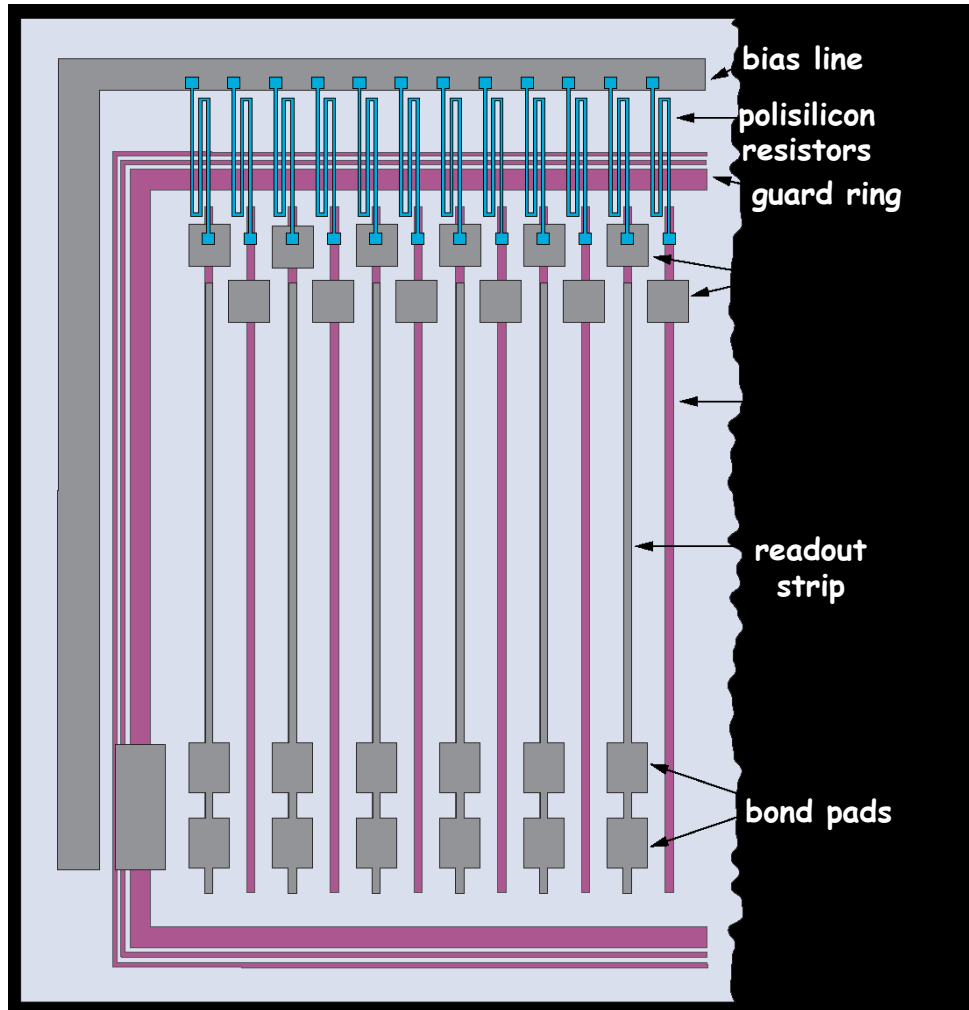
- ✓ about 30.000 e-h+ pairs in 300  $\mu\text{m}$  detector thickness
- ✓ p+n junction:  
 $N_a \approx 10^{15} \text{ cm}^{-3}$ ,  $N_d \approx 1-5 \cdot 10^{12} \text{ cm}^{-3}$
- ✓ n-type bulk:  $\rho > 2 \text{ k}\Omega\text{cm}$
- ✓ operating voltage  $< 200 \text{ V}$ .
- ✓ n+ layer on backplane to improve ohmic contact
- ✓ Aluminum metallization

Using p-type silicon and exchanging p+ and n+ would give a perfectly working p-type detector.

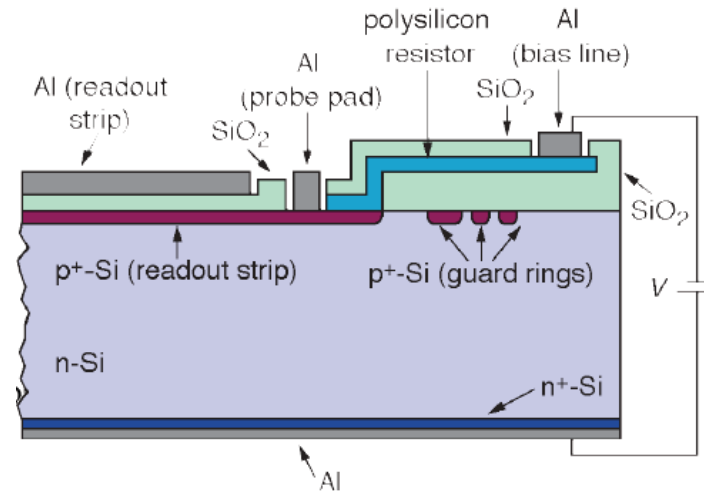
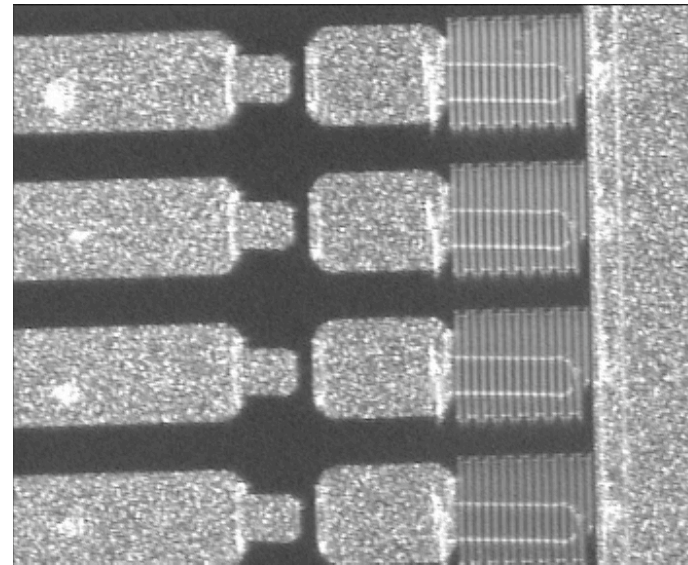
- Deposition of SiO<sub>2</sub> with a thickness of 100-200 nm between p+ and aluminum strip
- AC coupling blocks leakage current from the amplifier.
- Problems are shorts through the dielectric (pinholes). Usually avoided by a second layer of Si<sub>3</sub>N<sub>4</sub>.
- Need to isolate strips from each other to collect charge from each strip:  
several methods for high impedance bias voltage connection ( $\approx 1\text{M}\Omega$  resistor): polysilicon resistor, punch through bias, FOXFET bias.

# Detector Structures

Top view of a strip detector with polysilicon resistors:



CMS-Microstrip-Detector: Close view of area with polysilicon resistors, probe pads, strip ends.



# Biasing and AC coupling



## Bias resistor and AC Coupling

extra slide  
not shown

2b - Tracking with  
Solid State Detectors

### ■ Bias resistor

- Need to isolate strips from each other to collect/measure charge on each strip  
⇒ high impedance bias connection ( $\approx 1\text{M}\Omega$  resistor)

### ■ Coupling capacitor

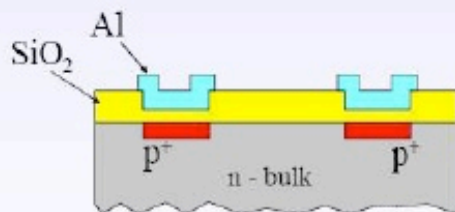
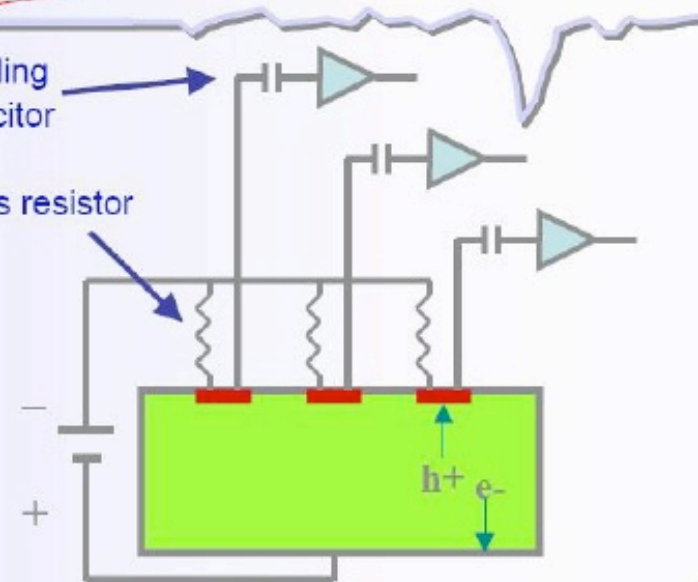
- Couple input amplifier through a capacitor (AC coupling) to avoid large DC input from leakage current

### ■ Integration of capacitors and resistors on sensor

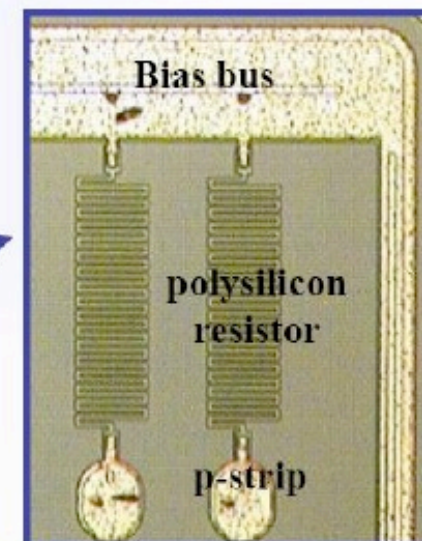
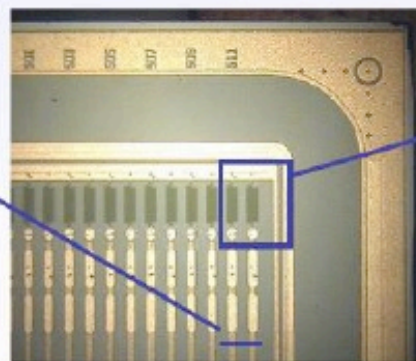
- Bias resistors via deposition of doped polysilicon
- Capacitors via metal readout lines over the implants but separated by an insulating dielectric layer ( $\text{SiO}_2, \text{Si}_3\text{N}_4$ ).

coupling  
capacitor

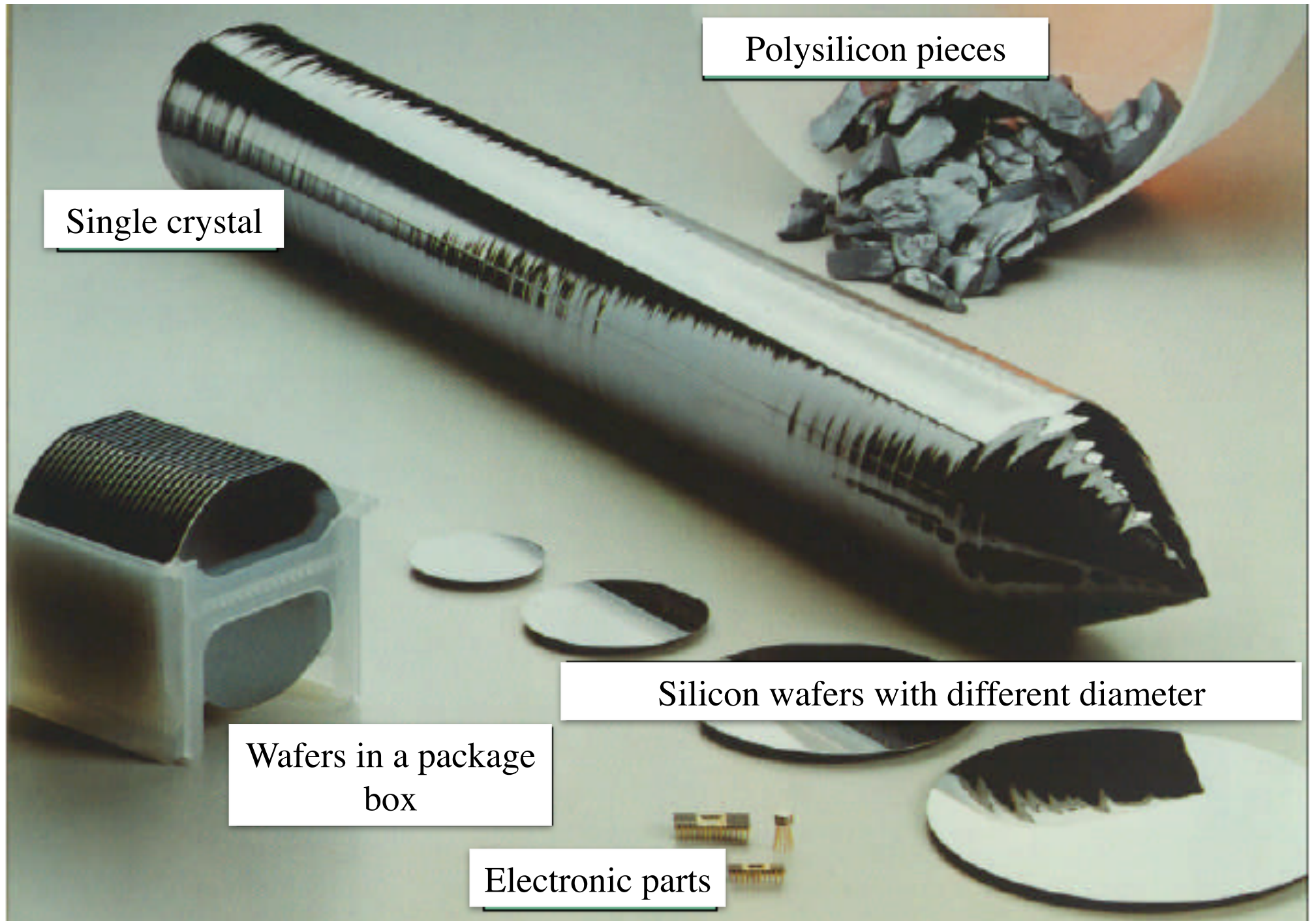
bias resistor



- ⇒ nice integration
- ⇒ more masks, processing steps
- ⇒ pin holes



CERN Academic Training Programme 2004/2005



Polysilicon pieces

Single crystal

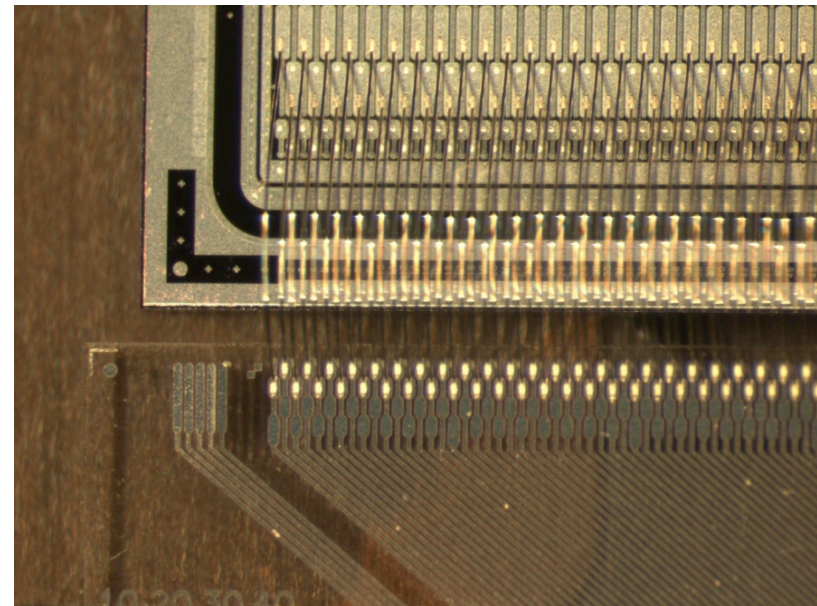
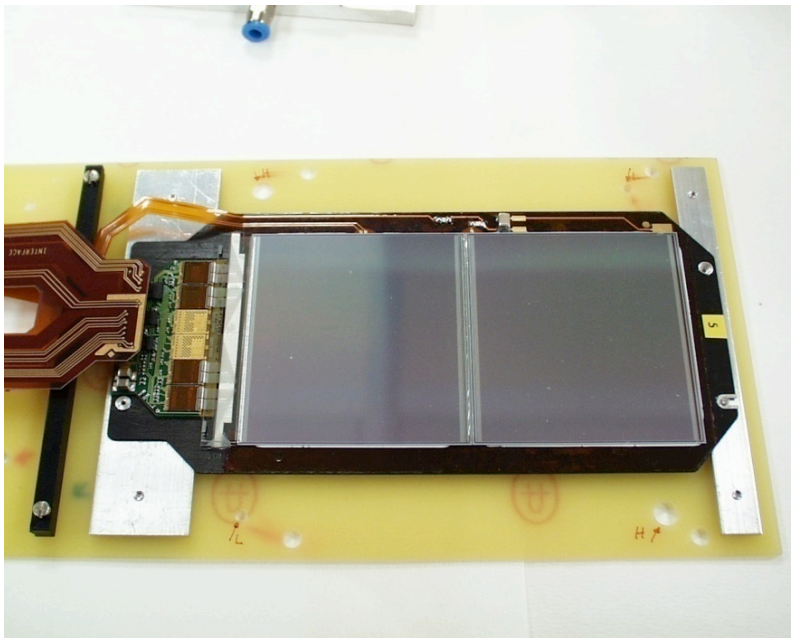
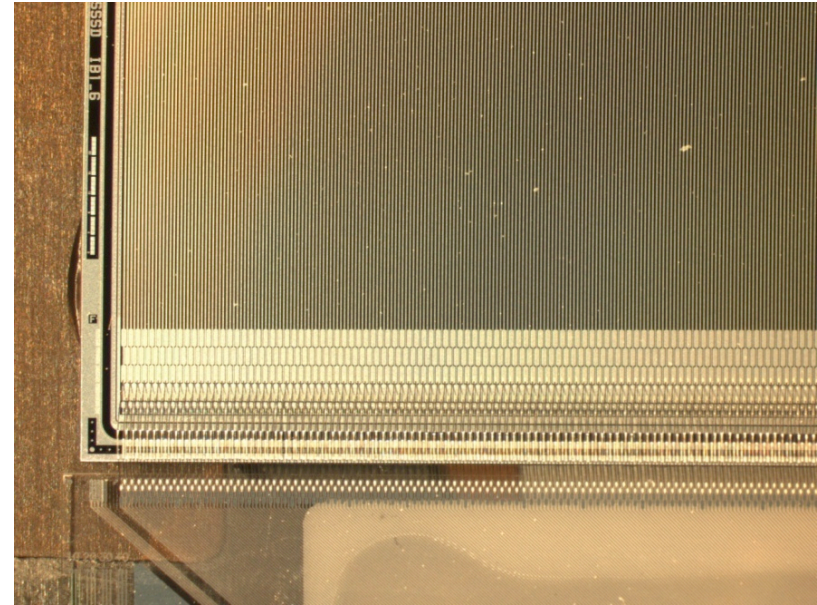
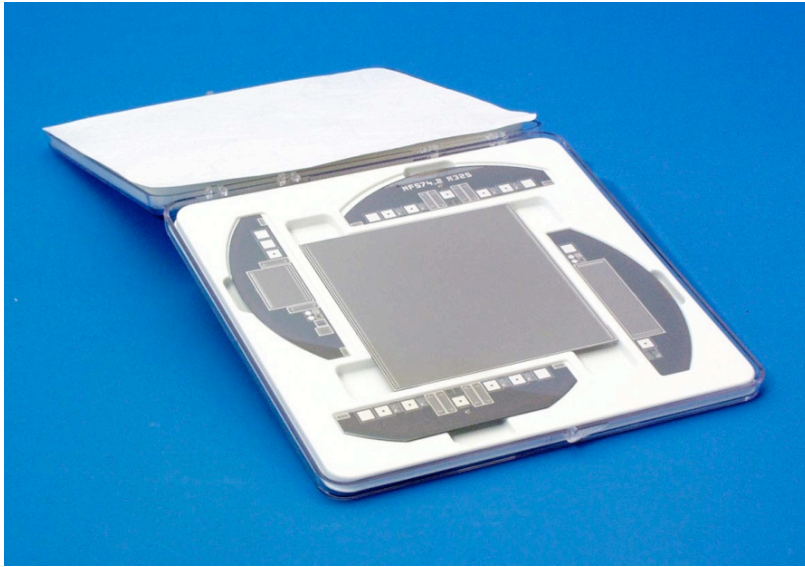
Silicon wafers with different diameter

Wafers in a package box

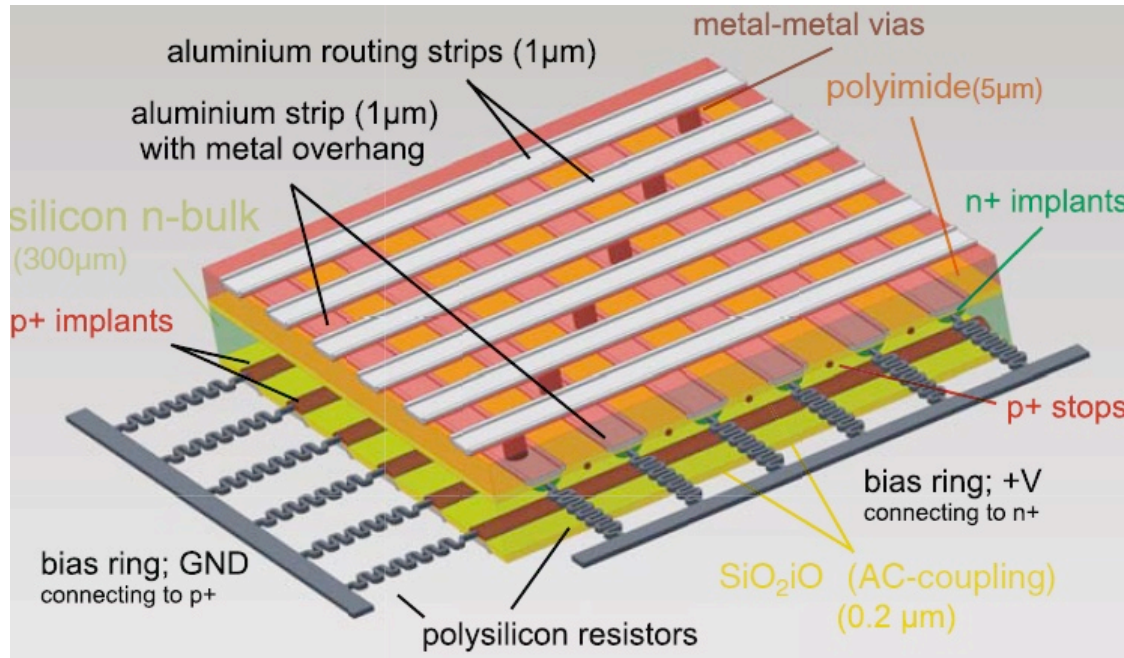
Electronic parts



# A CMS silicon strip detector built with a 6" wafer

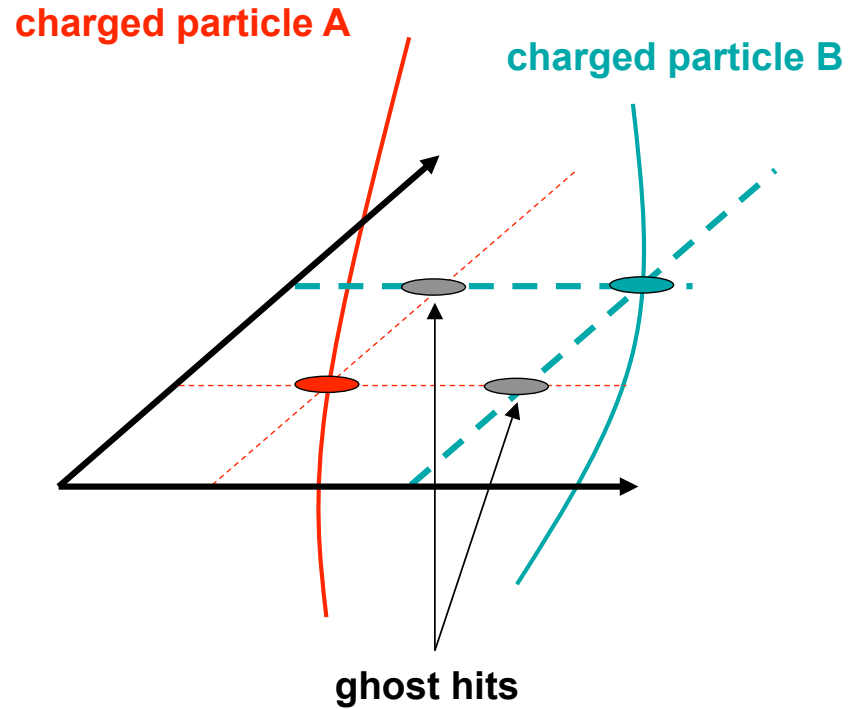


# Double Sided Strip Detectors



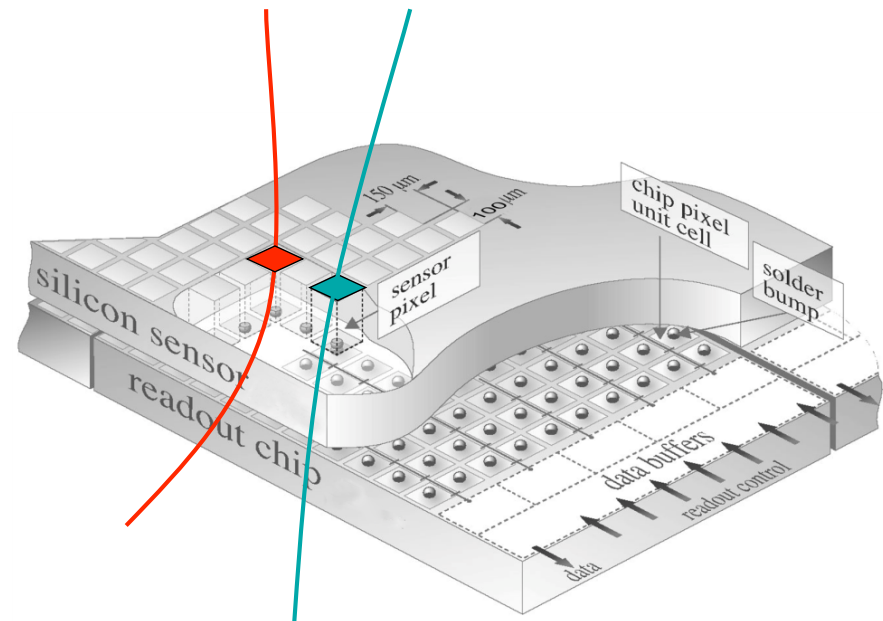
- ❖ Single sided strip detector measures only one coordinate. To measure second coordinate requires second detector layer.
- ❖ Double sided strip detector minimizes material measuring two coordinates in one detector layer.
- ❖ In n-type detector the n+ backside becomes segmented e.g. strips orthogonal to p+ strips.
- ❖ Drawback: Production, handling, tests are more complicated and hence double sided detector are expensive.

# Double Sided Strip Detectors



Double sided strip sensors measure the 2 dimensional position of a particle track. However, if more than one particle hits the strip detector the measured position is no longer unambiguous. "Ghost"-hits appear!

Pixel detectors produce 2-dimensional position measurements without ambiguity also in case of two particles crossing the detector!



# Pixel Detectors

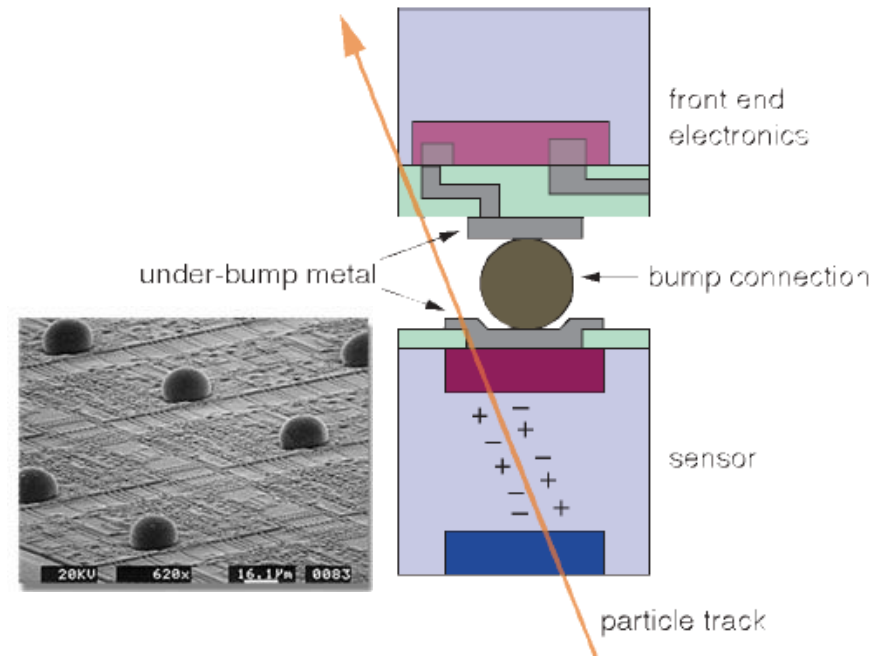
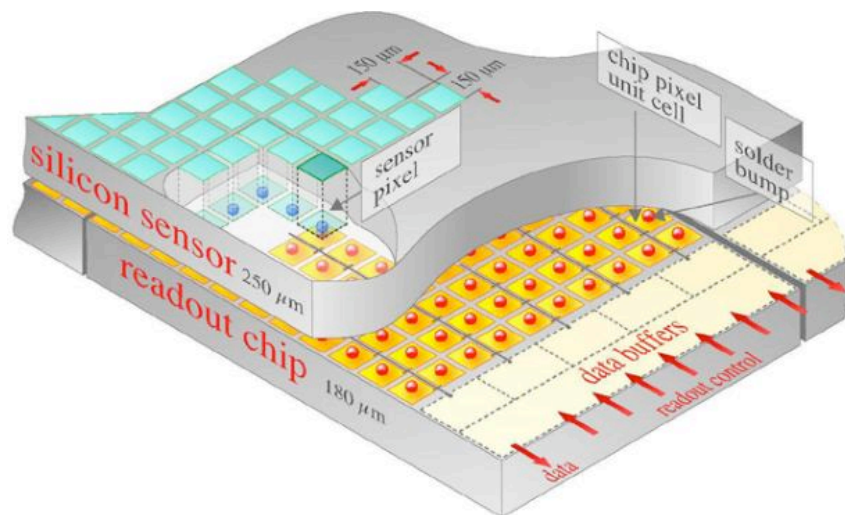
- Typical pixel size  $50 \times 200 \mu\text{m}^2$ ;  $100 \times 100 \mu\text{m}^2$ :
  - Small pixel area  $\rightarrow$  low detector capacitance ( $\approx 1 \text{ fF/Pixel}$ )  
 $\rightarrow$  large signal-to-noise ratio (e.g. 150:1).
  - Small pixel volume  $\rightarrow$  low leakage current ( $\approx 1 \text{ pA/Pixel}$ )
- Large number of readout channels:
  - Large number of electrical connections
  - Large power consumption of electronics

Problem:

Coupling of readout electronics to the detector

Solution:

Bump bonding



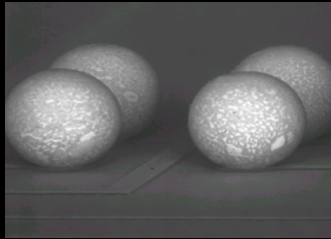
# Pixel Detector Module Breakdown



PP0 connection

Flex Hybrid

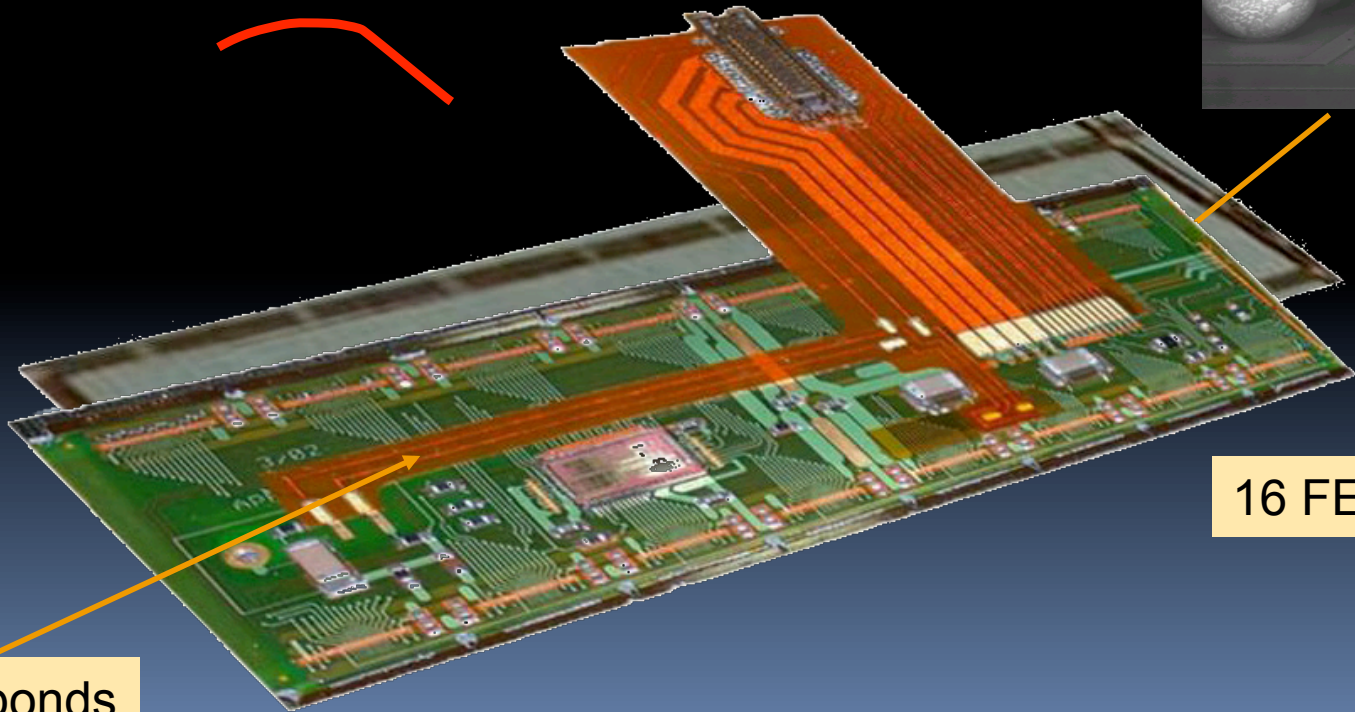
Bump bonds



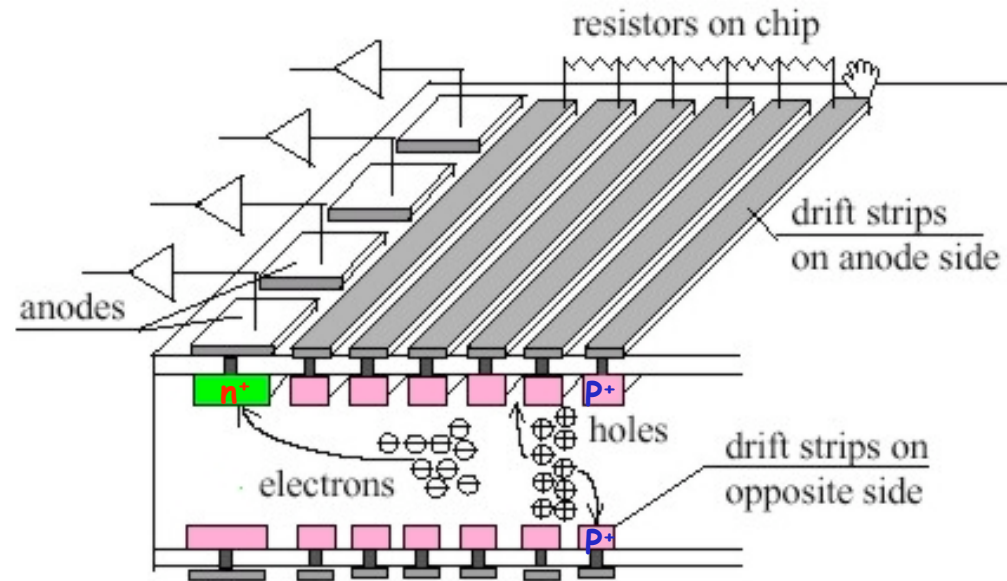
Sensor tile

16 FE chips

Wire bonds



# Silicon Drift Detector (like gas TPC !)

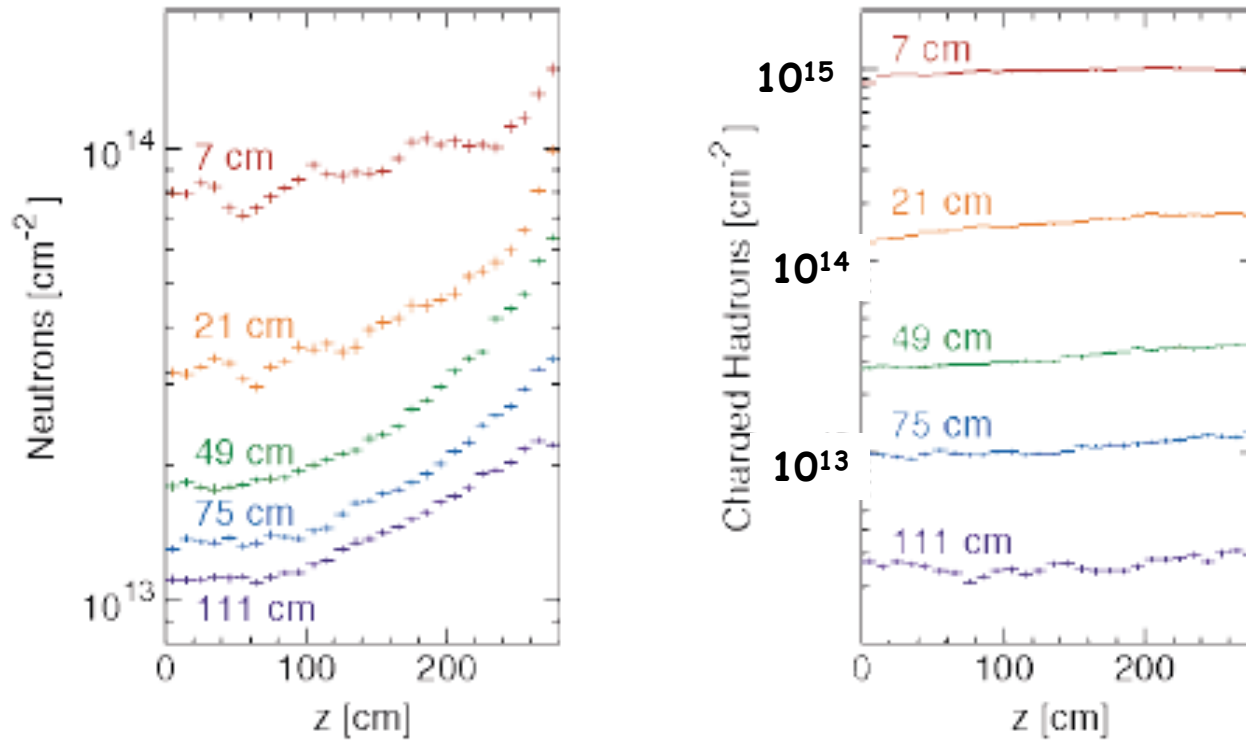


In silicon drift detectors the p+ strips and the backplane p+ implantation are used to fully deplete the bulk.

A drift field transports the generated electrons to the readout electrodes (n+).

One coordinate is measured by signals on strips, the second by the drift time.

# Radiation environment at the LHC



Expected particle fluences for the silicon detector inner layers in CMS integrated over 10 years as a function of the distance from the vertex point and for various radii.

Left: neutrons

Right: charged hadrons

# Radiation damage

Particles (radiation) interact with atoms of the detector material and may cause permanent changes (defects) in the detector bulk.

## ■ One distinguishes two types of radiation damage:

- damage inside the detector bulk (bulk damage): dislocated atoms from their position in the lattice caused by massive particles.
  - Bulk damage is primarily produced by neutrons, protons and pions.
- damage introduced in the surface layers (surface damage) is due to the charges generated in the amorphous oxide
  - Surface damage is primarily produced by photons and charged particles.

## ■ Defects may change with time:

- one distinguishes between primary defects and secondary defects
- the secondary defects appear with time caused by moving primary defects

## ■ Cumulative effects:

- increased leakage current
- silicon bulk type inversion (n-type to p-type)
- increased depletion voltage
- increased capacitance

## ■ Sensor can stop working :

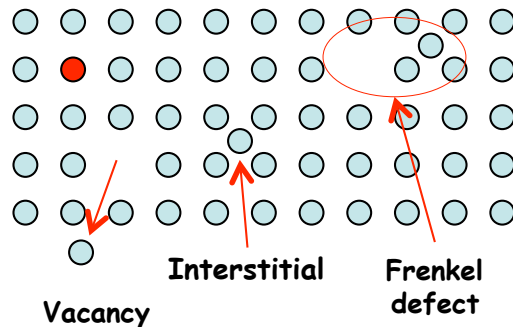
- noise too high
- depletion voltage too high
- loss of inter-strip isolation

Typical limits of Si Detectors are at  $10^{14}$ - $10^{15}$  Hadrons/cm<sup>2</sup>

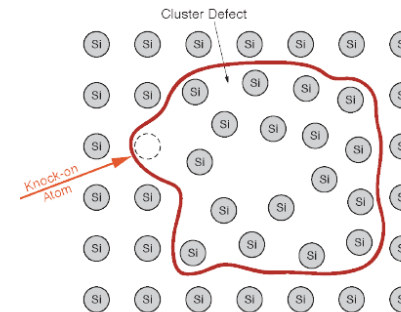


# Radiation damage

- Defects in the semiconductor lattice create energy levels in the band gap between valence and conduction band. Depending on the position of these energy levels the following effects will occur:
  - Modification of the effective doping concentration  
→ shift of the value of the depletion voltage.
  - Trapping of charge carriers  
→ reduced lifetime of charge carriers
  - Easier thermal excitement of  $e^-$  and  $h^+$   
→ increase of the leakage current



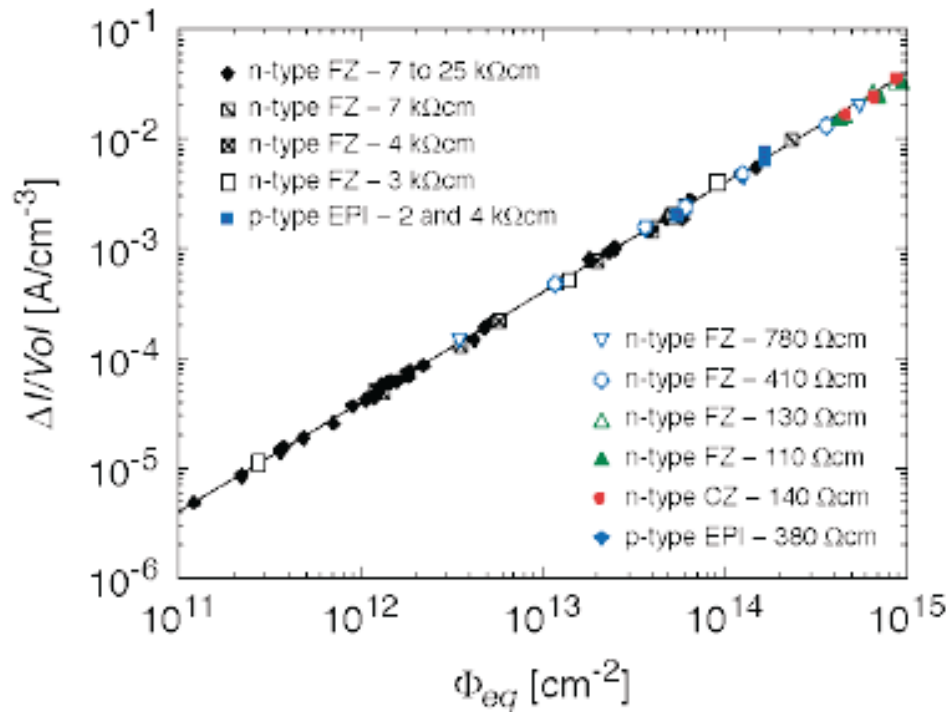
A displaced silicon atom produces an empty space in the lattice (Vacancy) and in another place an atom in an inter-lattice space (Interstitial, I). A vacancy-interstitial pair is called a Frenkel-defect.



In hard impacts the primary knock-on atom displaces additional atoms. These defects are called cluster defects. The size of a cluster defect is approximately 5 nm and consists of about 100 dislocated atoms.

# Radiation damage

Increase of leakage current as function of irradiation fluence (different materials)



In ten years of LHC operation the currents of the innermost layers increase by 3 orders of magnitude!

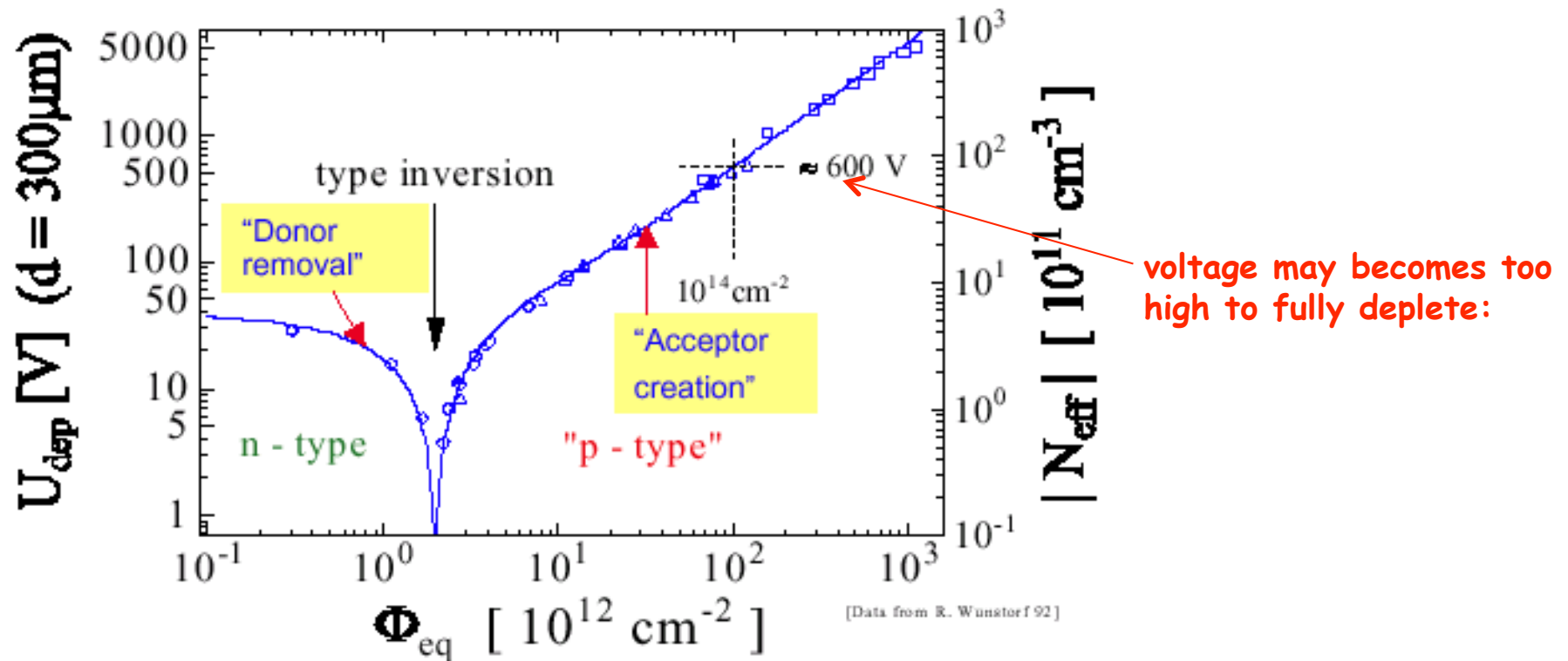
$$\bullet \Delta I = \alpha \Phi_{eq} V$$

$\alpha$  damage constant  $\approx 3 \times 10^{-17}$  A/cm

M. Moll, *Radiation Damage in Silicon Particle Detectors*,  
PhD-Thesis (1999)

# Radiation damage

Full depletion voltage and effective doping concentration of an originally n type silicon detector as a function of the fluence  $\Phi_{eq}$ :



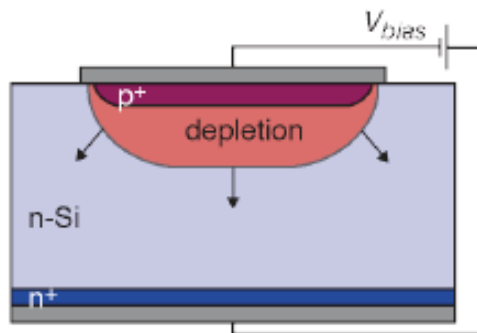
Type inversion ! an n-type Si detector becomes a p-type Si detector !

# Radiation damage

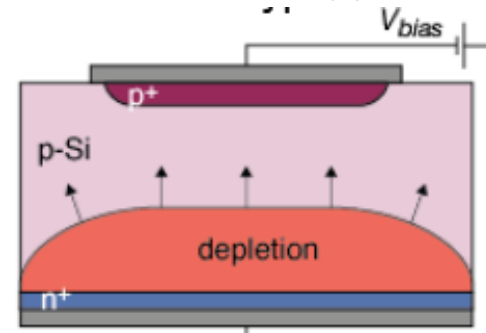
In n type sensors with p+ implants the depletion zone grows from the p+ implants to the backplane n+ implant.

After type inversion the p+ bulk is now depleted from the backside (polarity of bias voltage remains the same)

Unirradiated detector:



Detector after type inversion:

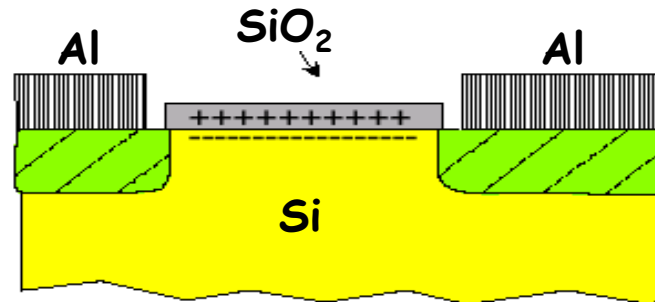


n-type detectors before type inversion can be operated below full depletion

after type inversion, the depletion zone has to reach the strips.

(a possible solution is to use n+p or n+n detectors)

## Surface defects in the oxide



- ❑ Ionizing radiation creates charges in the oxide  
(in the amorphous oxide dislocation of atoms is not relevant)
- ❑ The mobility of electrons in SiO<sub>2</sub> is much larger than the mobility of holes
  - electrons diffuse out of the oxide, holes remain semi permanent fixed
  - the oxide becomes positively charged due to these fixed oxide charges.
- Consequences for the detector:
  - ✓ reduced electrical separation between implants
  - ✓ increase of interstrip capacitance
  - ✓ increase of detector noise
  - ✓ worsening of position resolution
  - ✓ increase of surface leakage current
  - ✓ reduced break down voltage

# CREDITS

Several drawings of this presentation have been borrowed (sometimes with small changes only for the sake of my presentation) from very good lectures that can be found in the Web.

See for instance:

W. Riegler; Summer Student Lectures 2009

M. Krammer; XI ICFA School on Instrumentation